

# Generate Renewable Energy Efficiently using Nanofabricated Silicon (GREEN Silicon)

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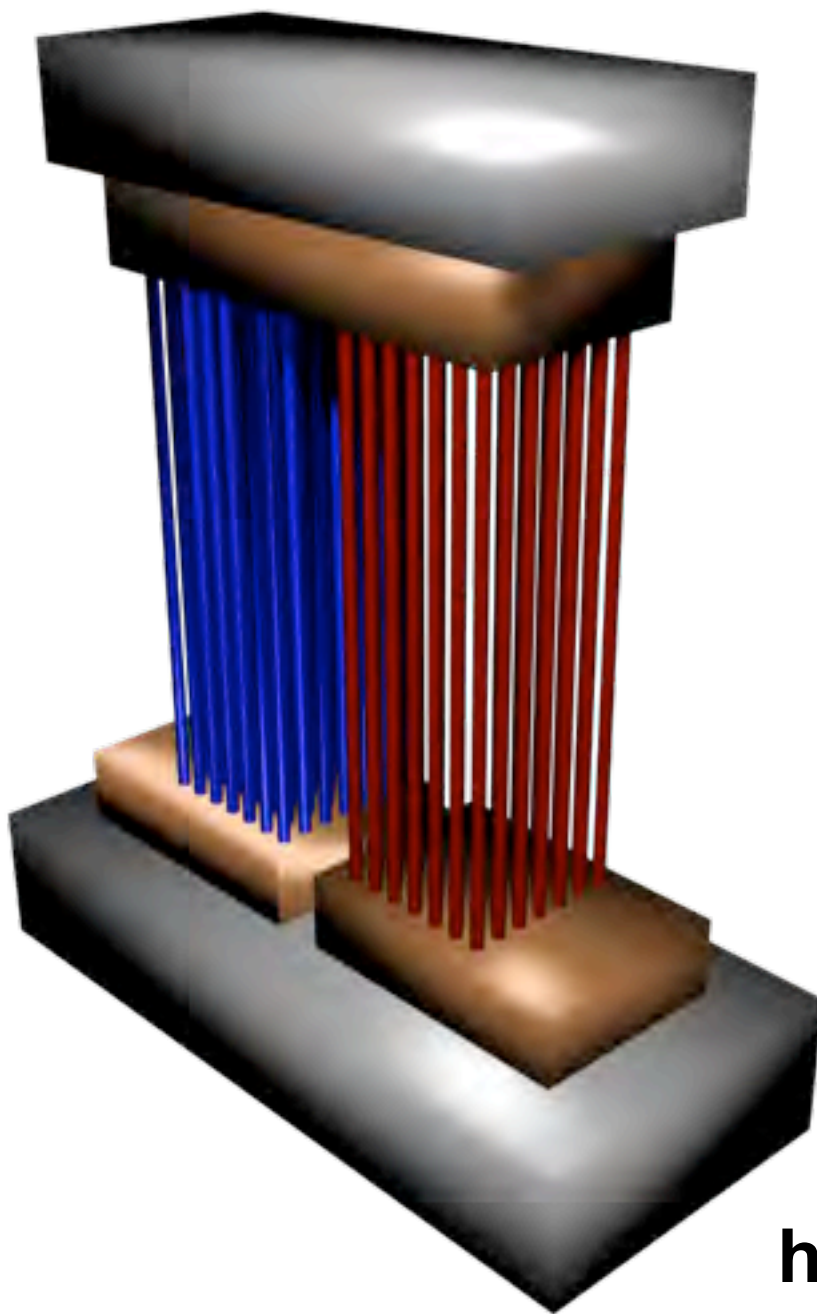
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**University of Linz, Austria**

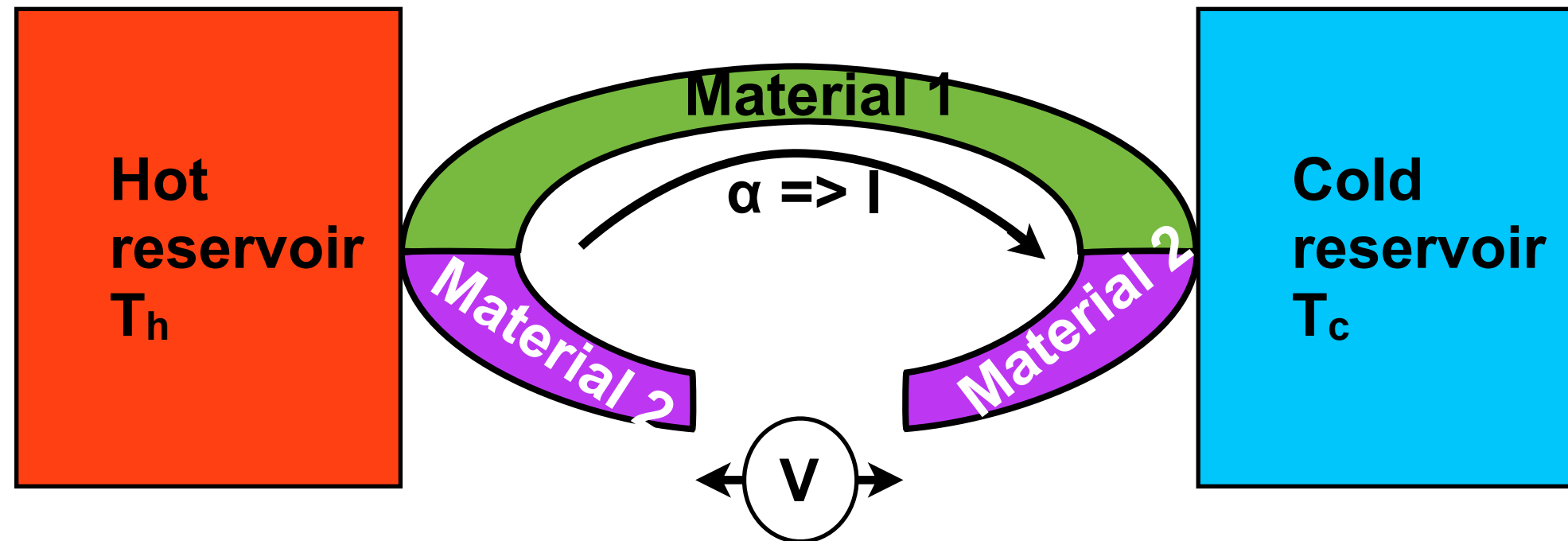
**E. Müller & H. von Känel**

**ETH Zürich, Switzerland**



**<http://www.greensilicon.eu/GREENSilicon/index.html>**

# The Seebeck Effect



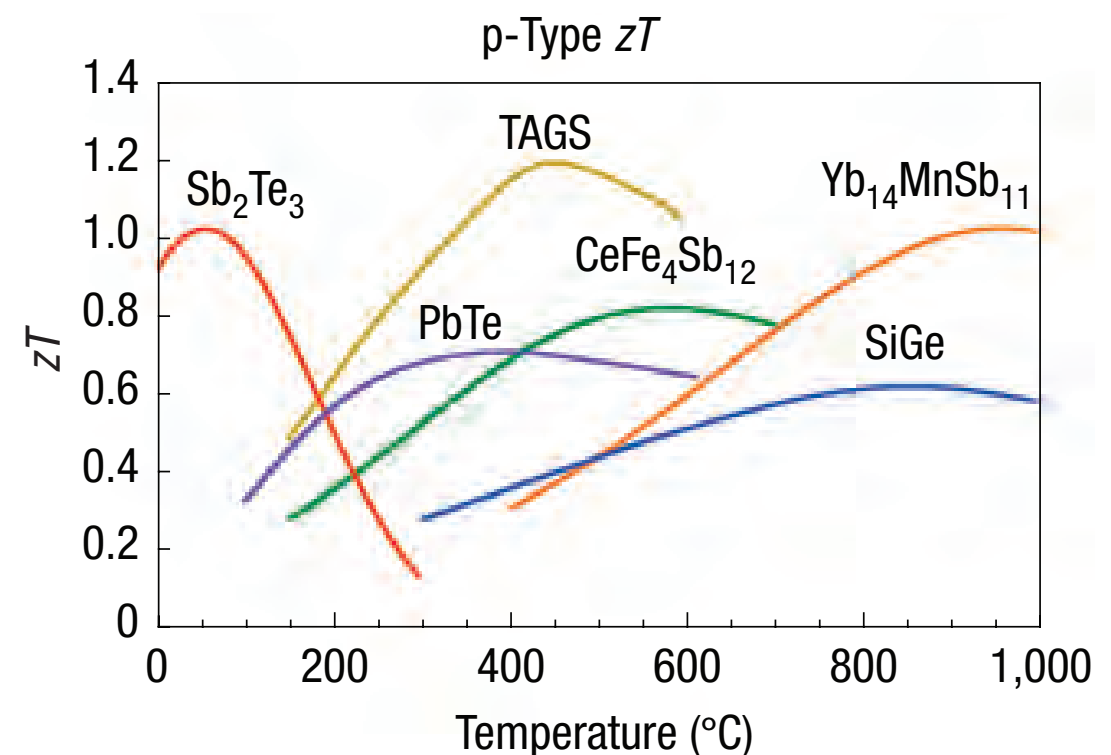
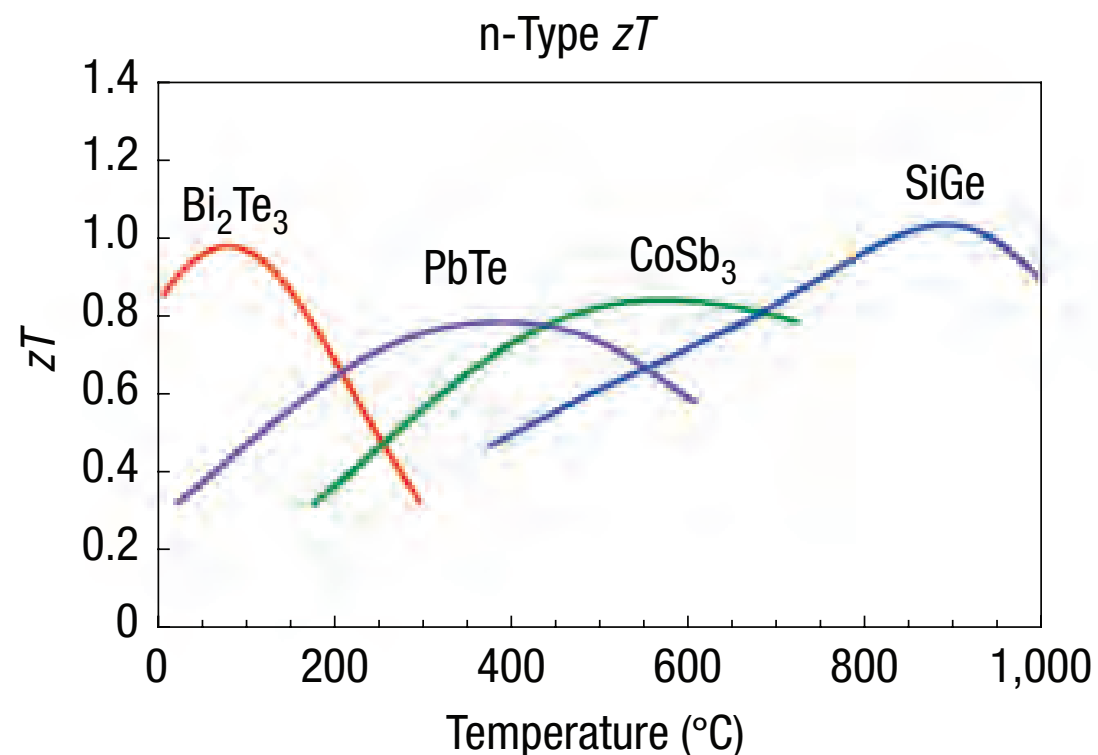
- Open circuit voltage,  $V = \alpha (T_h - T_c) = \alpha \Delta T$

$$\text{Seebeck coefficient, } \alpha = \frac{dV}{dT}$$

units: V/K

- Seebeck coefficient =  $\frac{1}{q}$  x entropy  $\left(\frac{Q}{T}\right)$  transported with charge carrier

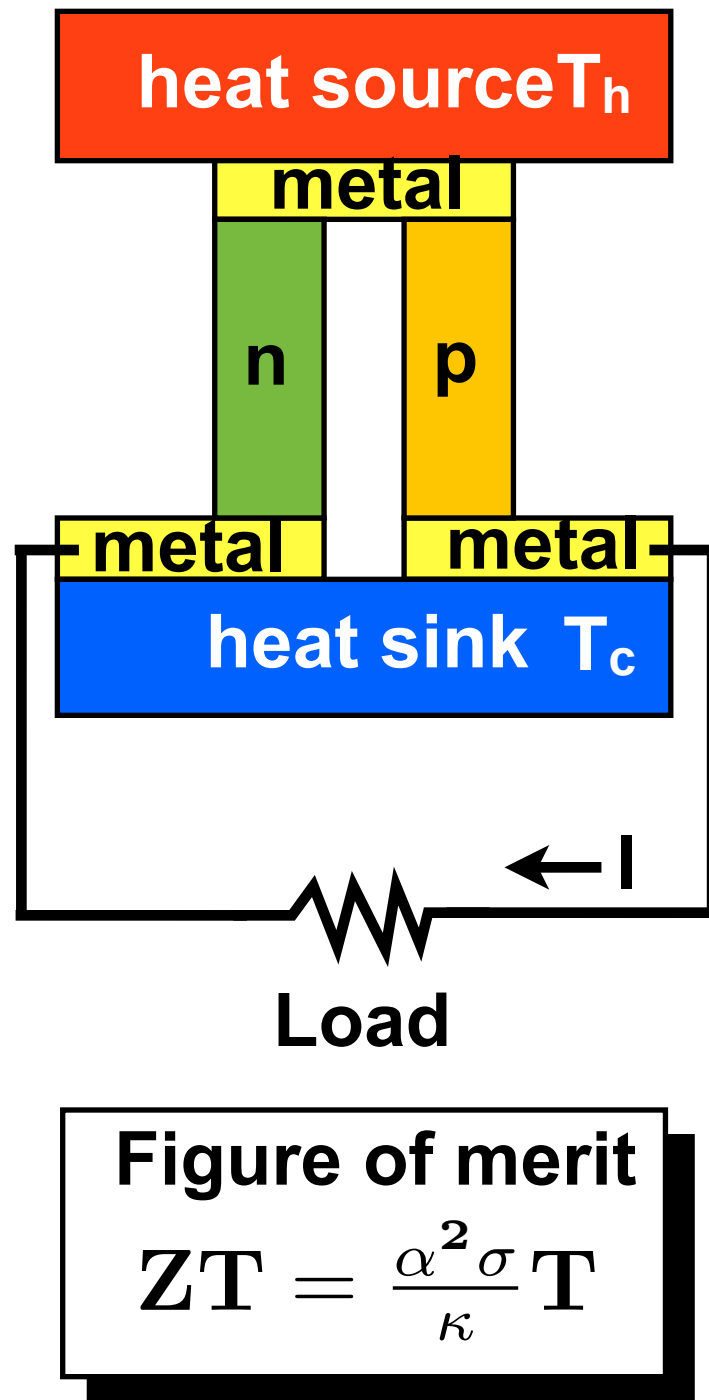
# Bulk Thermoelectric Materials Performance



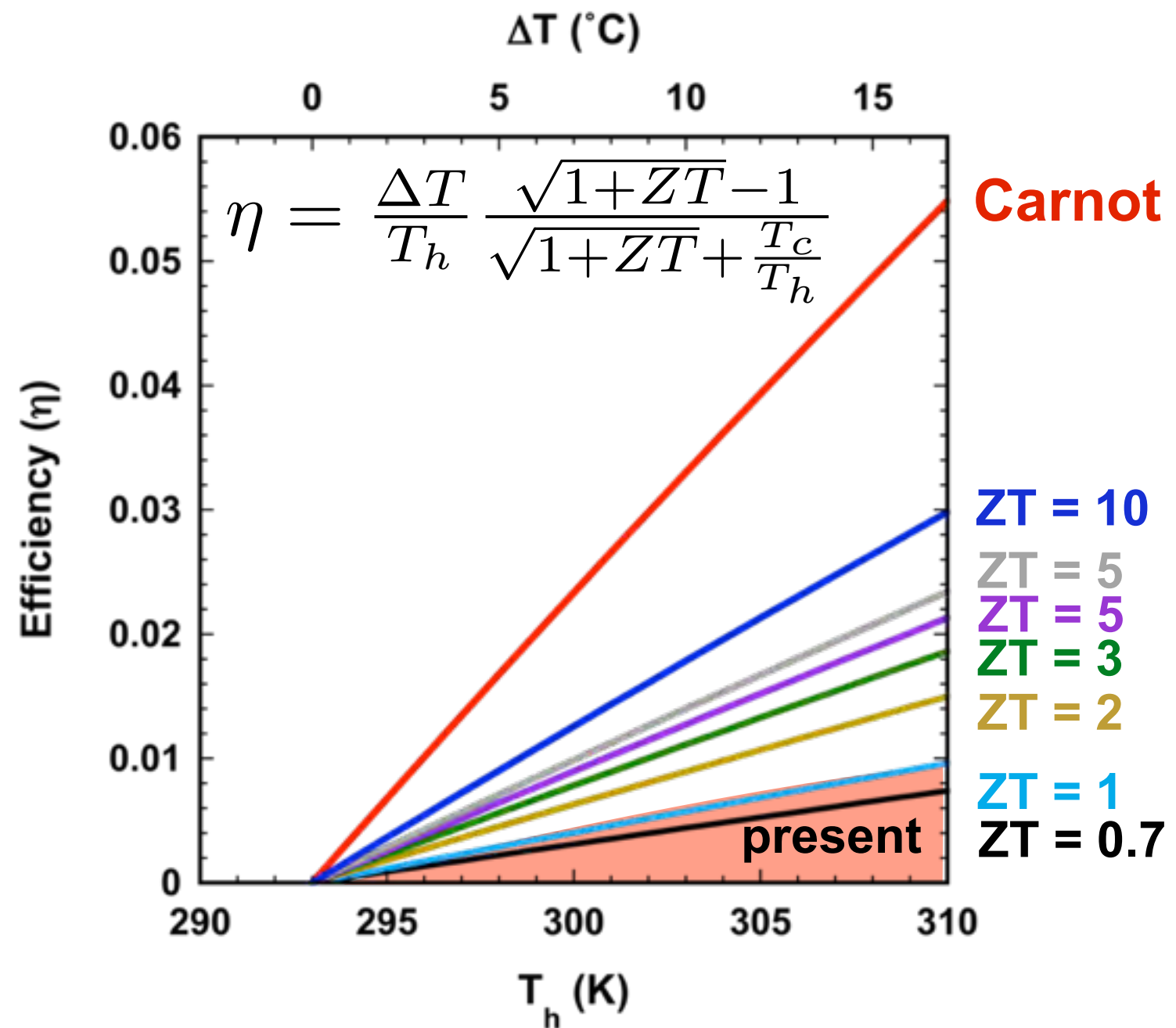
*Nature Materials 7, 105 (2008)*

- Bulk n- $\text{Bi}_2\text{Te}_3$  and p- $\text{Sb}_2\text{Te}_3$  used in most commercial thermoelectrics & Peltier coolers
- But tellurium is 8<sup>th</sup> rarest element on earth !!!
- Bulk  $\text{Si}_{1-x}\text{Ge}_x$  ( $x \sim 0.2$  to  $0.3$ ) used for high temperature satellite applications

# Thermoelectric Power Generating Efficiency



Power factor =  $\alpha^2 \sigma$



Impedance matching and maximum power point tracking are key for thermoelectrics

# GREEN Silicon: Objectives

**Overall Aim: to use nanofabrication with phonon and bandgap engineering to produce cheap, efficient thermoelectric on-chip generators**

**Technology push / application pull:**

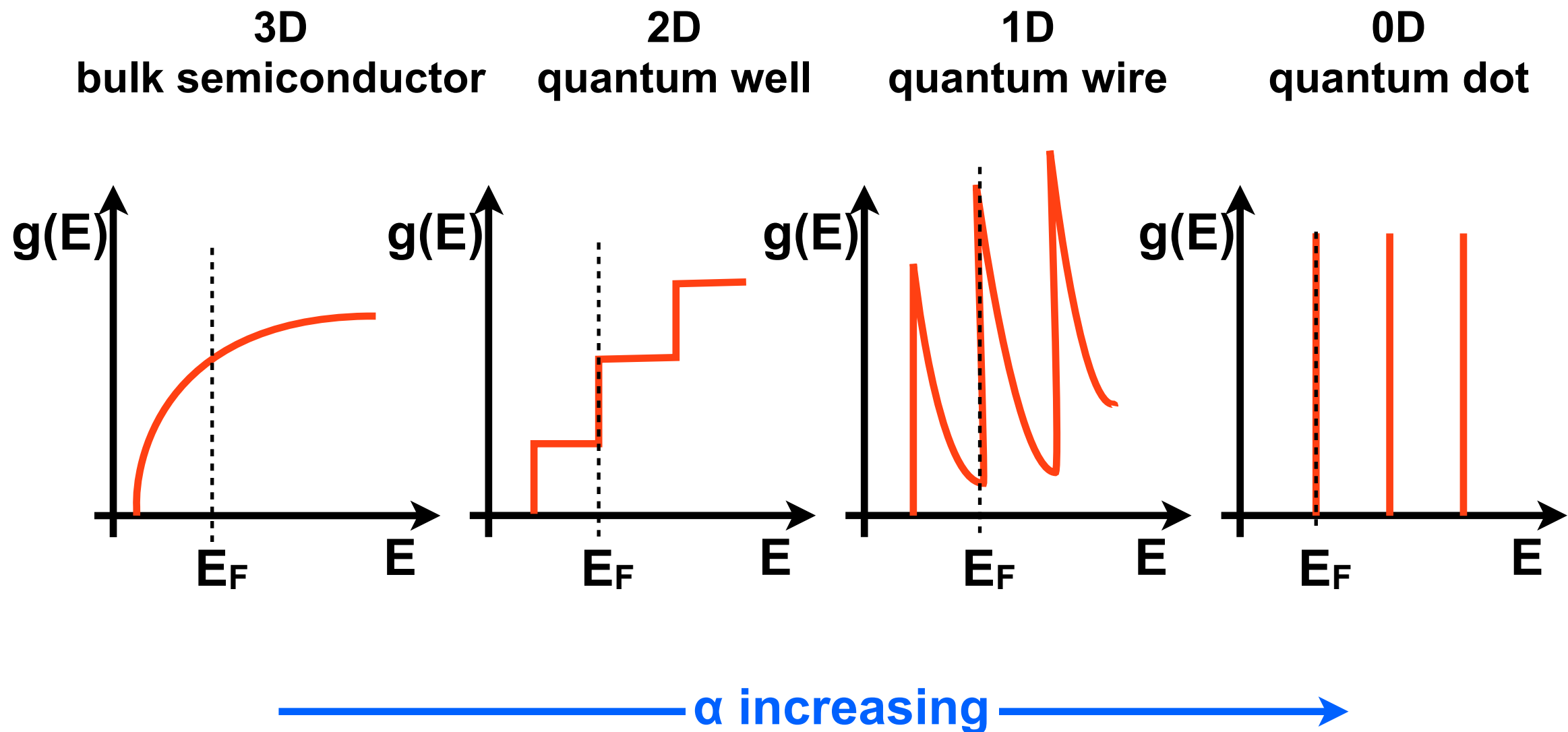
- **Si/SiGe/Ge heterostructures for back-end CMOS process → on-chip**
- **Engineer properties using superlattices, 0D quantum dots and 1D nanowires**
- **Micro- and nano-fabrication technologies for thermoelectric modules**
- **Combine modelling, growth, fabrication and characterisation to optimise power output**



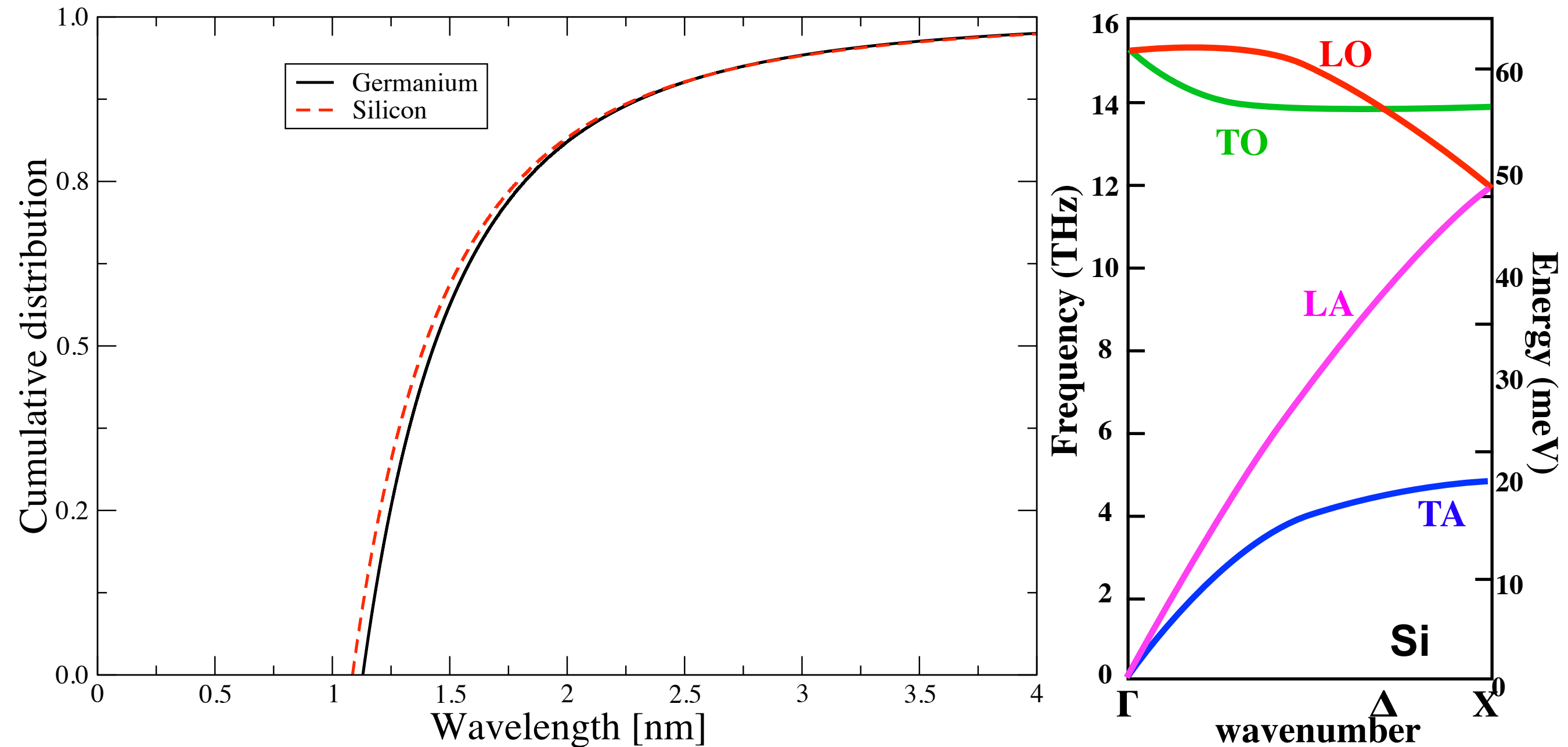
# Seebeck Enhancement at Low Dimensions

- Increase  $\alpha$  through enhanced DOS:

$$\alpha = -\frac{\pi^2}{3q} k_B^2 T \left[ \frac{d \ln(\mu(E)g(E))}{dE} \right]_{E=E_F}$$



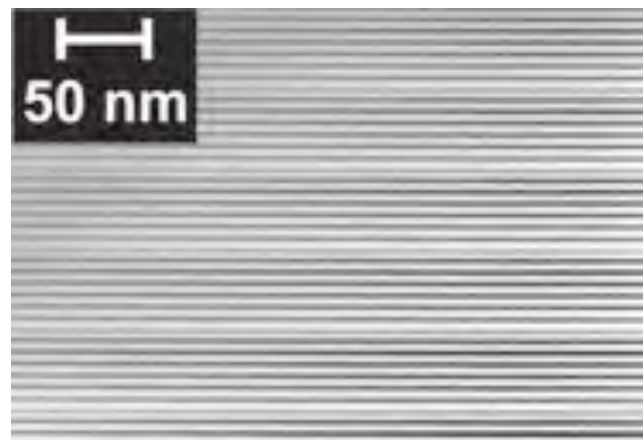
# Phonon Wavelengths that Carry Heat



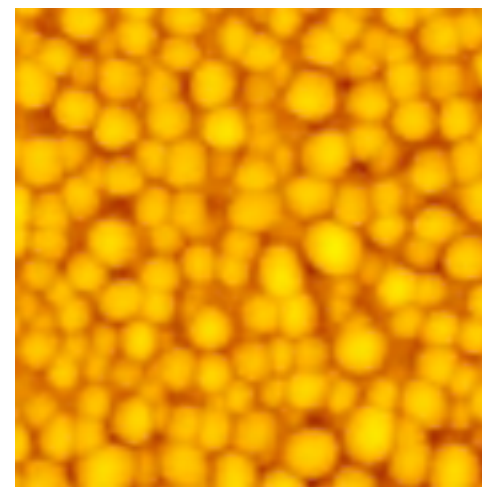
- Greater than 95% of heat conduction in Si / Ge from acoustic phonons with wavelengths between 1.2 and 3.5 nm

# GREEN Silicon Approach and Vision

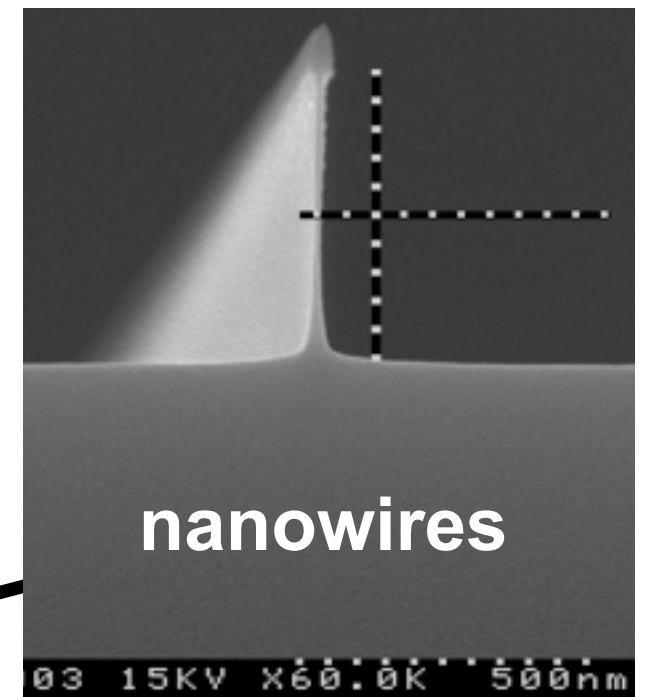
**Low  
dimension  
technology**



**superlattices**

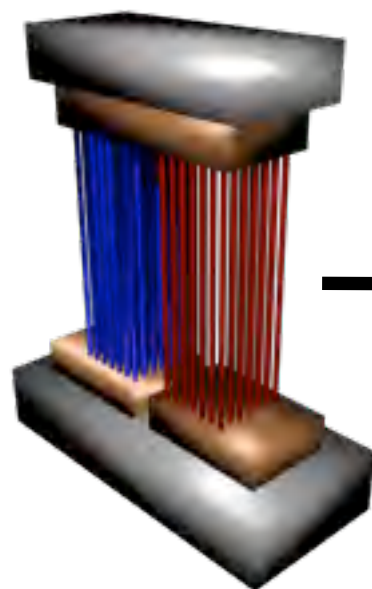


**quantum dots**

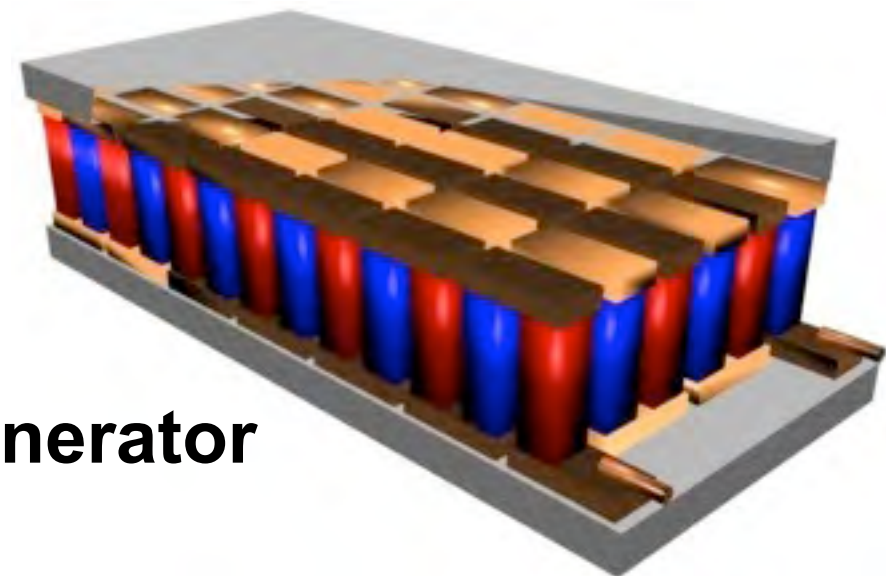


**nanowires**

**Module**



**Generator**

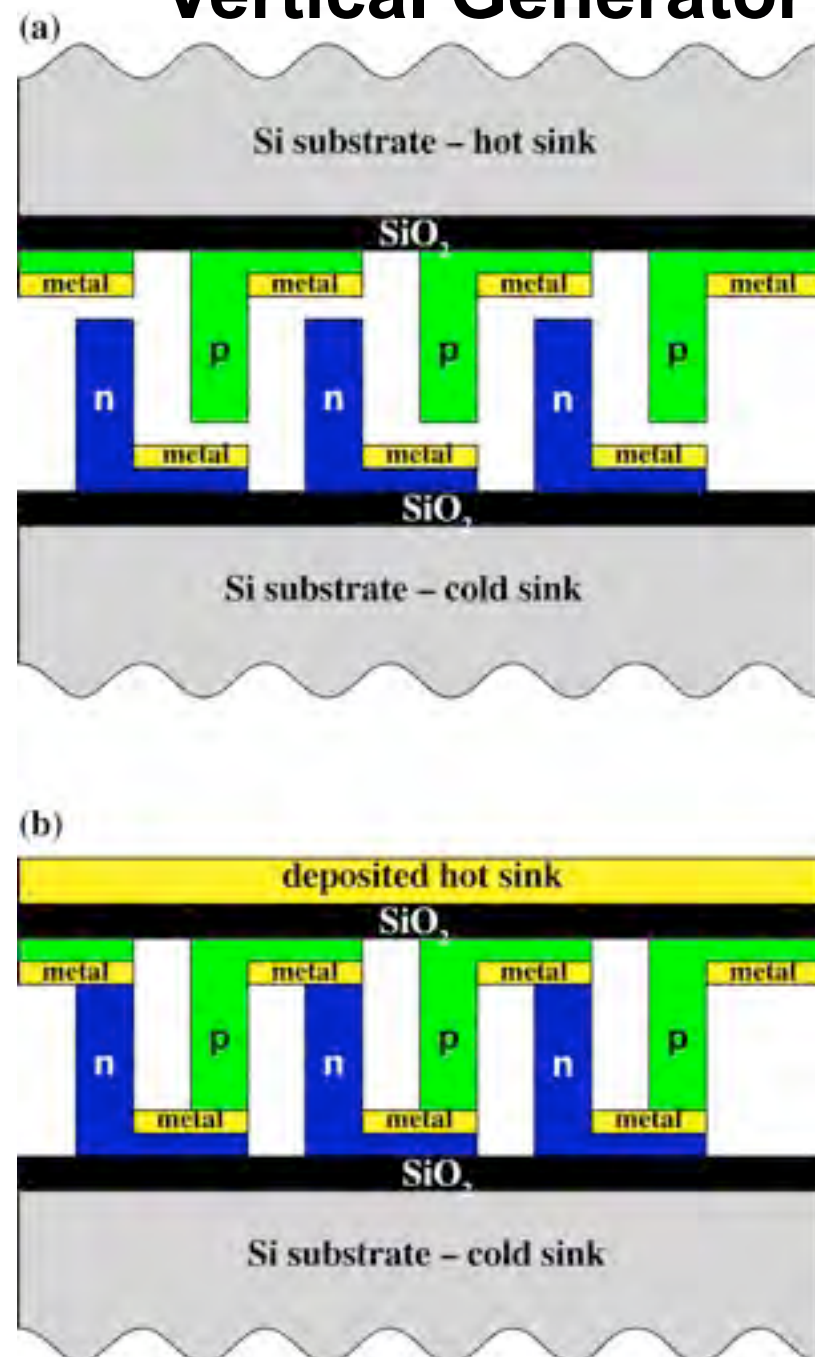


● **Si/SiGe technology → cheap and back end of line compatible**

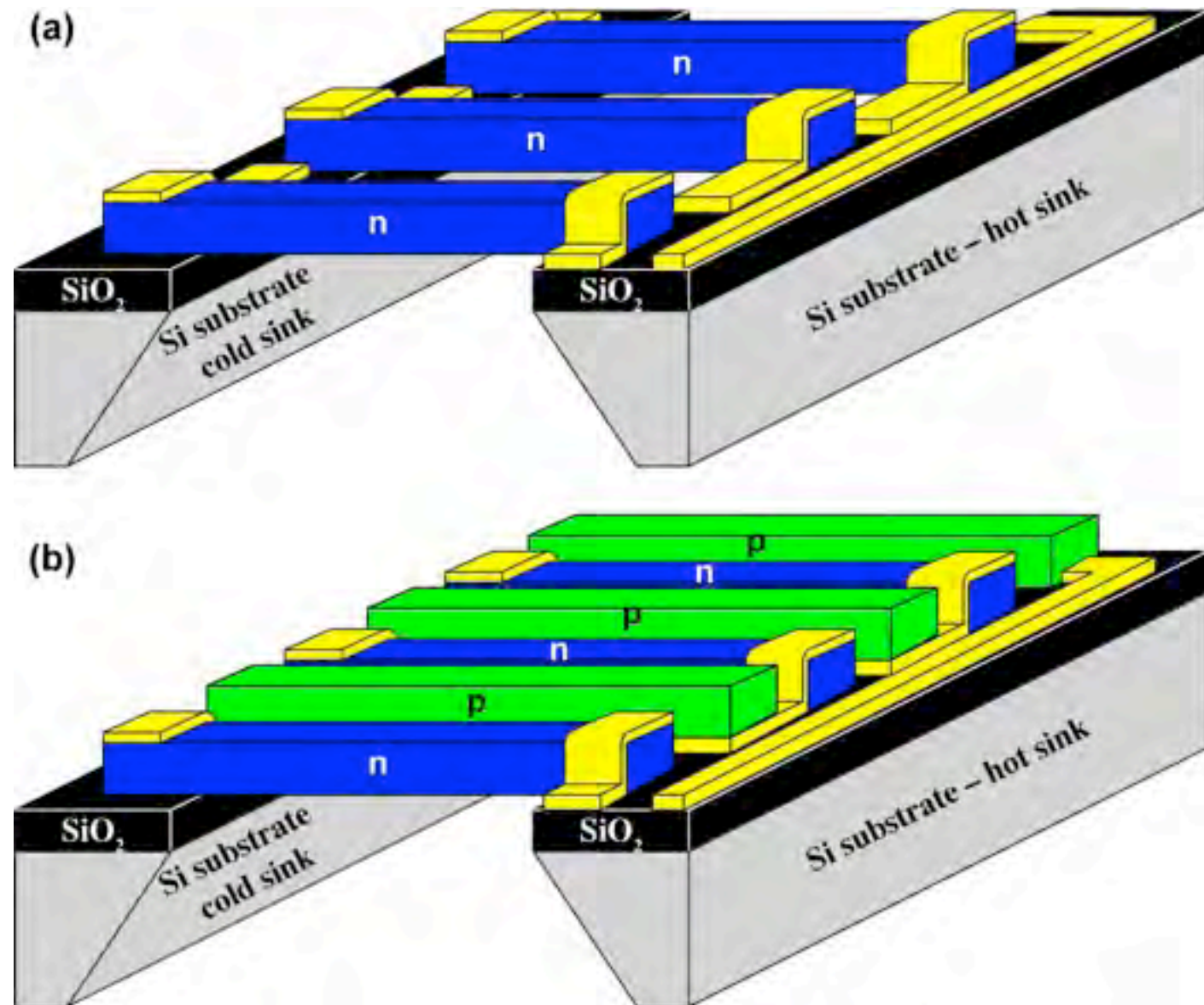


# Wafer Scale Microfabrication of Generators

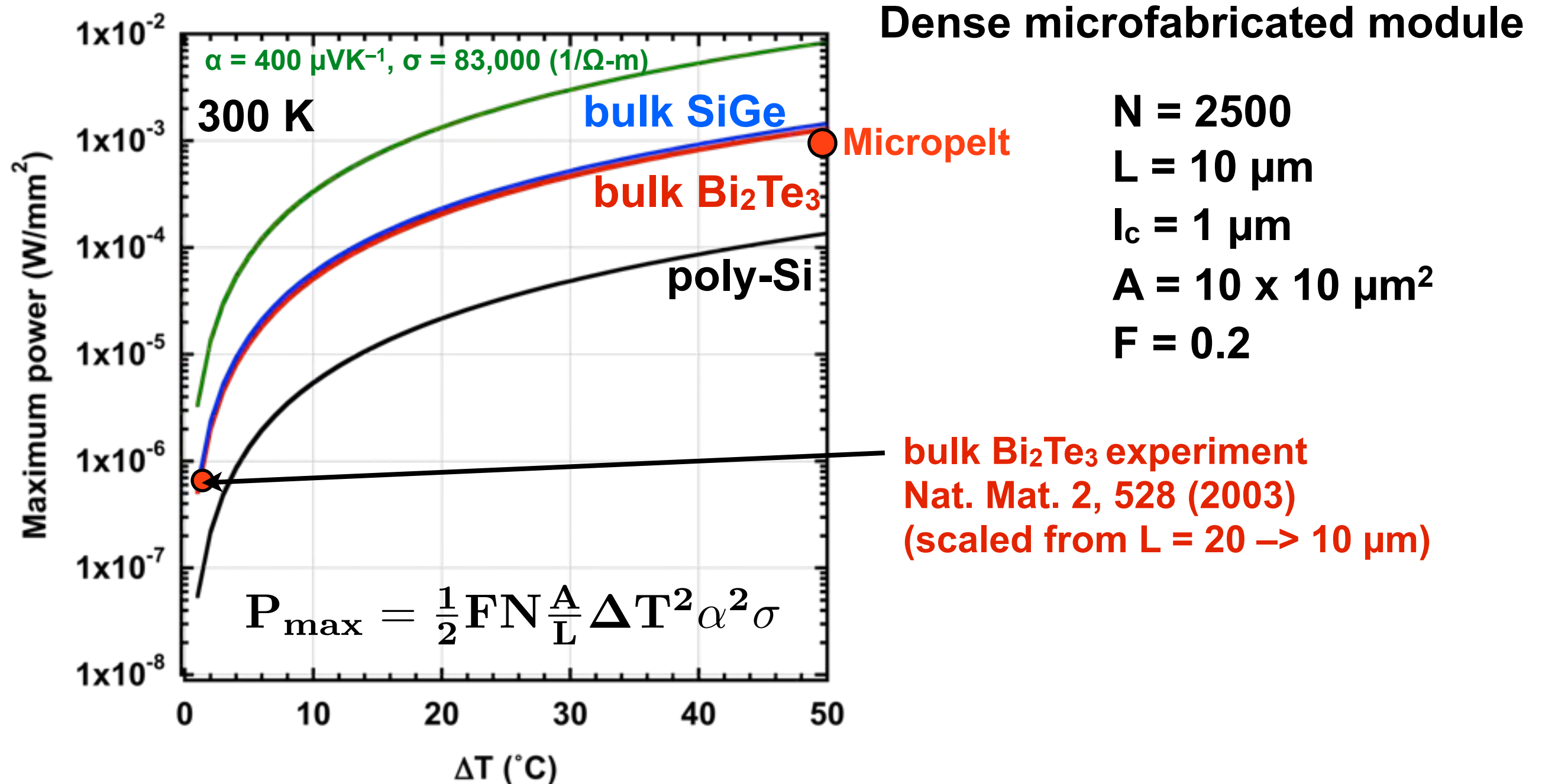
## Vertical Generator



## Lateral Generator



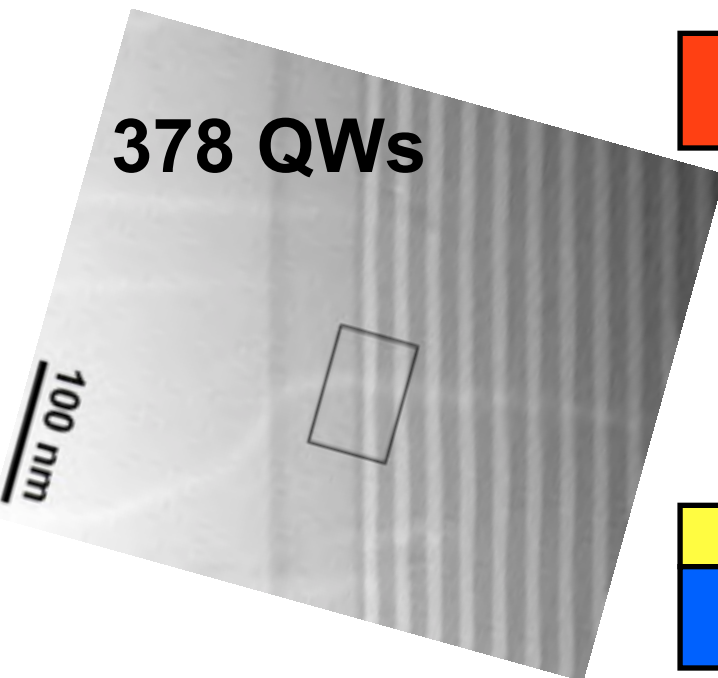
# Maximum Power Estimations: Optimisation



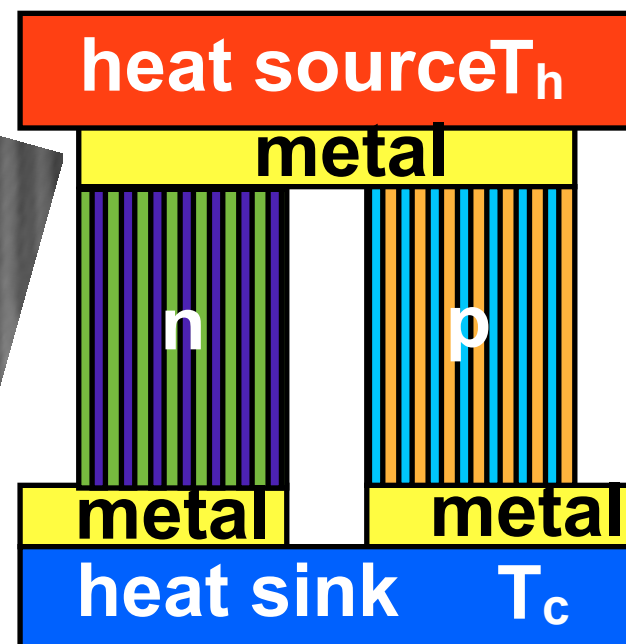
**N.B. The thermal conductivity must also be considered for  $\Delta T_{\text{max}}$  but not for the maximum power!**



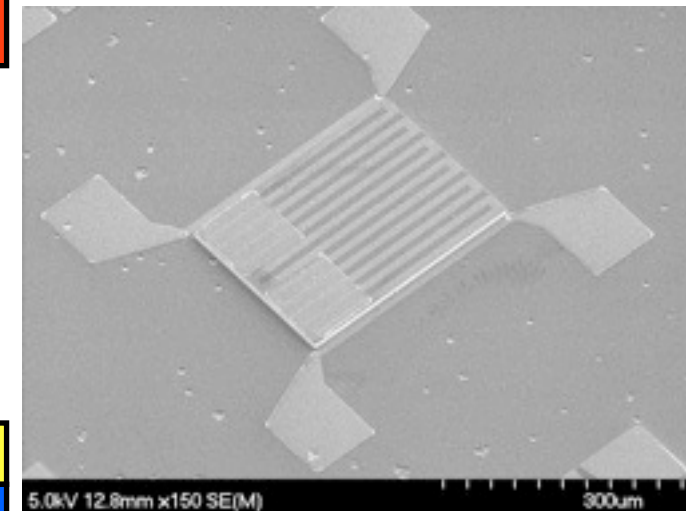
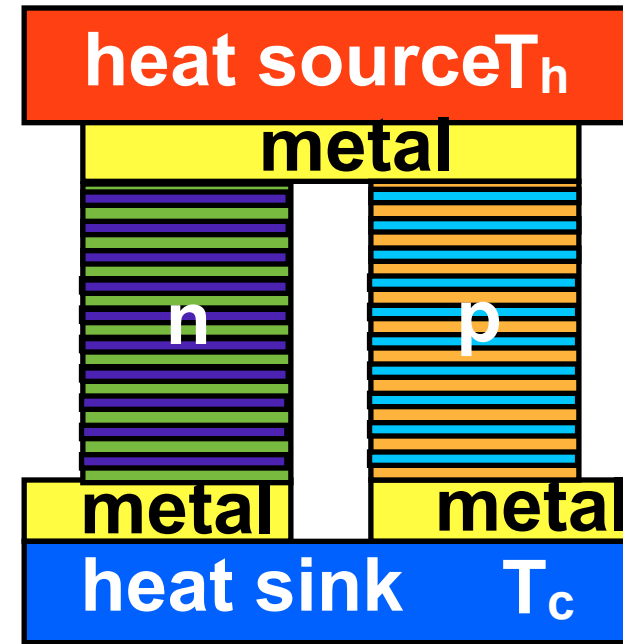
# Thermoelectric Low Dimensional Structures



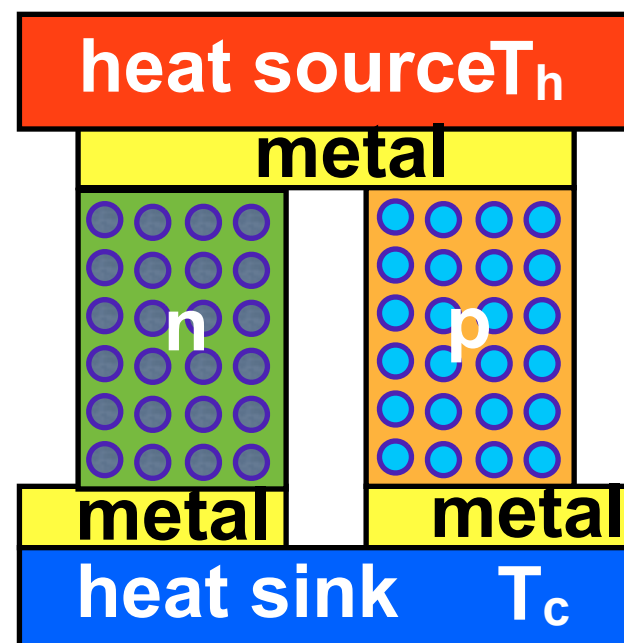
## Lateral superlattice



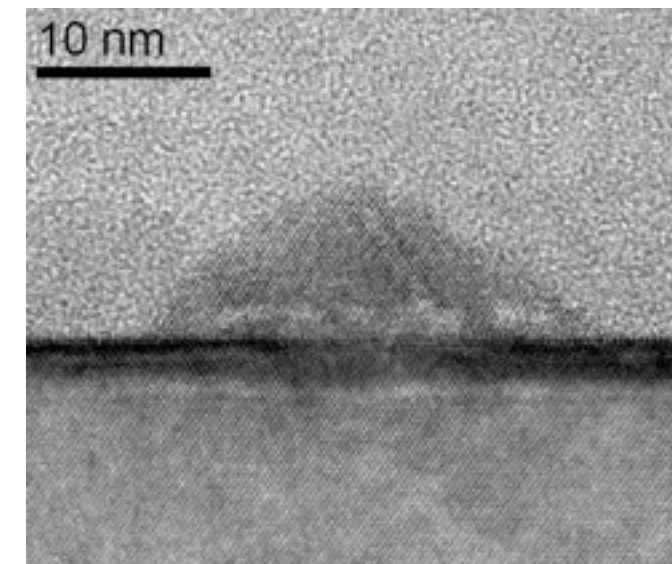
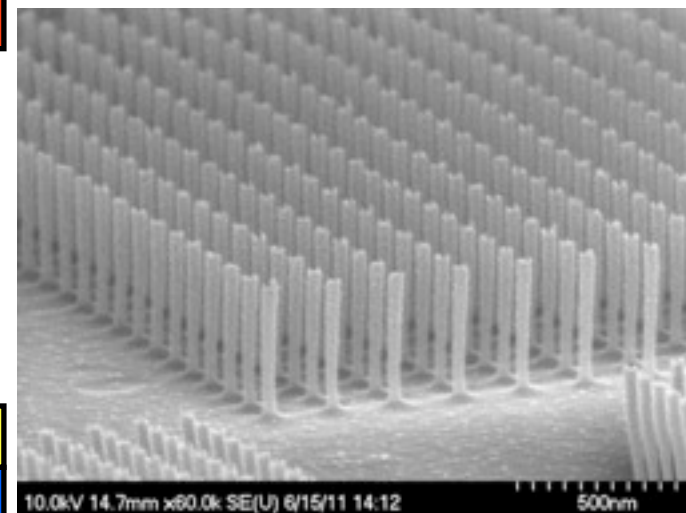
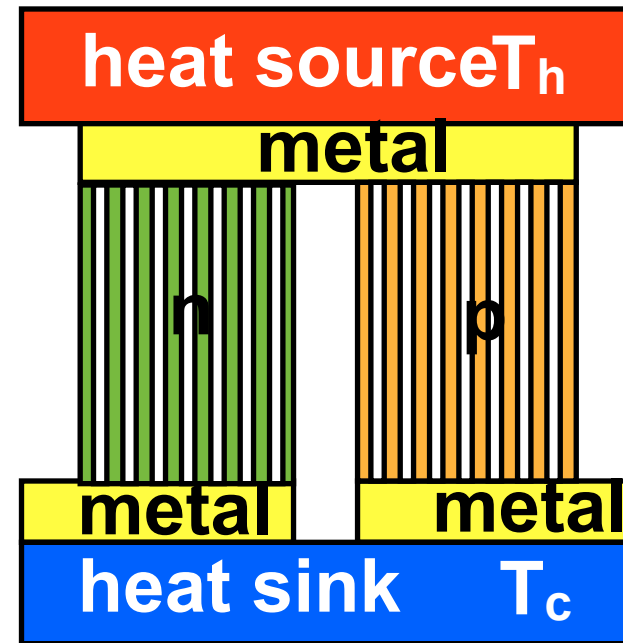
## Vertical superlattice



## Quantum Dots



## Nanowires



# Low Dimensional Structures: 2D Superlattices

- Use of transport along superlattice quantum wells
- Higher  $\alpha$  from the higher density of states
- Higher electron mobility in quantum well  $\rightarrow$  higher  $\sigma$
- Lower  $\kappa_{ph}$  through additional phonon scattering from heterointerfaces
- Disadvantage: higher  $\kappa_{el}$  with higher  $\sigma$  (but layered structure can reduce this effect)
- Overall  $Z$  and  $ZT$  should increase

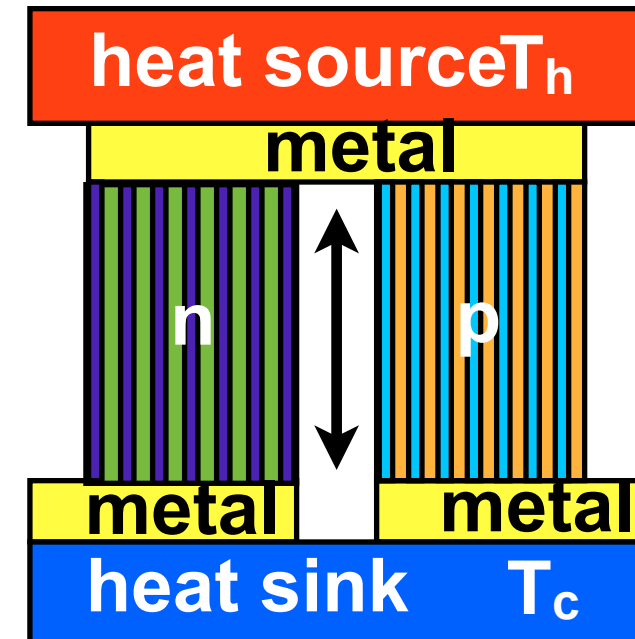


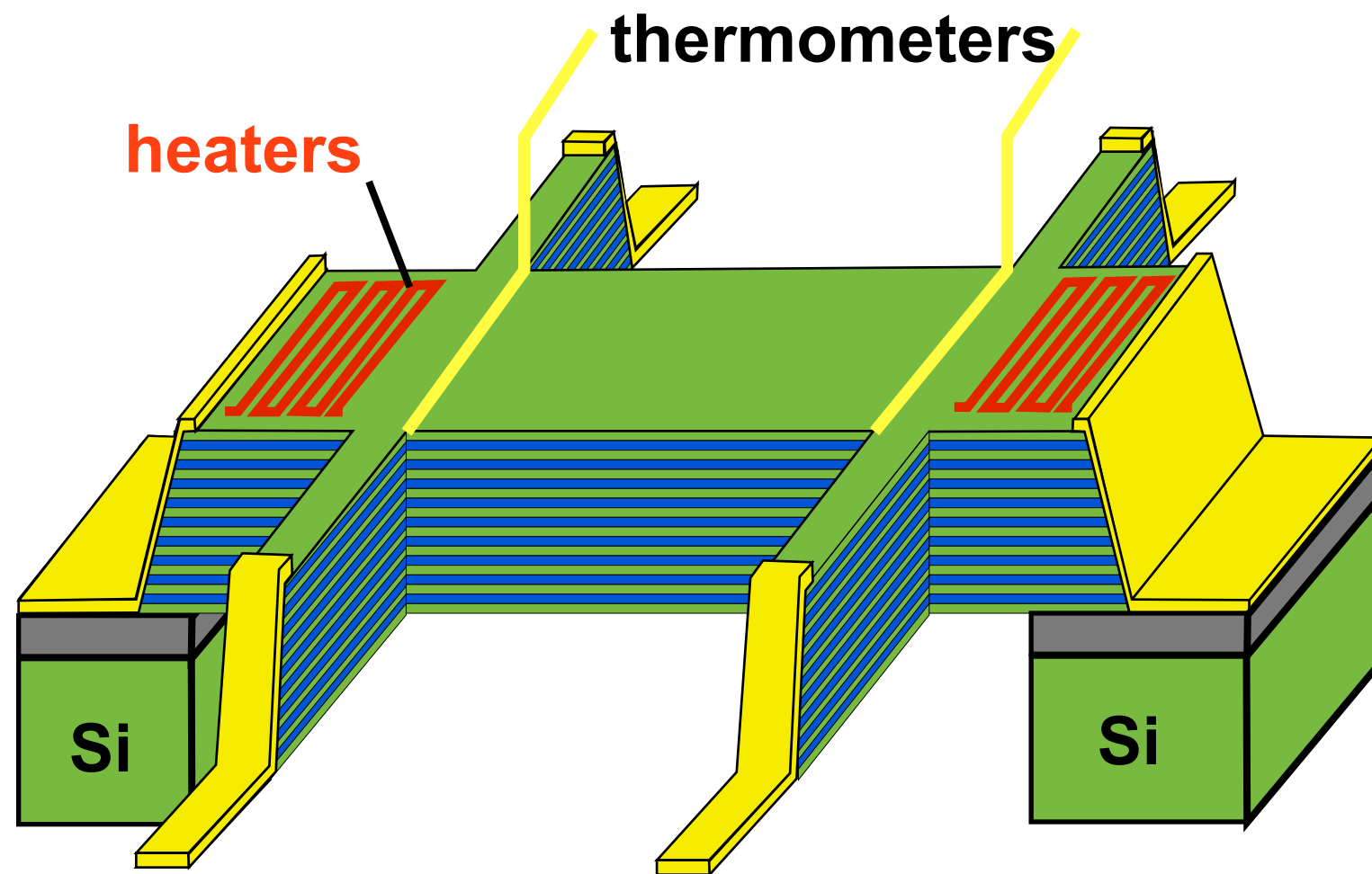
Figure of merit

$$ZT = \frac{\alpha^2 \sigma}{\kappa} T$$

*EHC Parker and TE Whall, 1987*

*L.D. Hicks and M.S. Dresselhaus, Phys. Rev. B 47, 12737 (1993)*

# Measuring Lateral $\alpha$ , $\sigma$ , $\kappa$ and ZT



● Hall bar geometry

● Heat transport easier to model

● Accurate electrical measurements easy

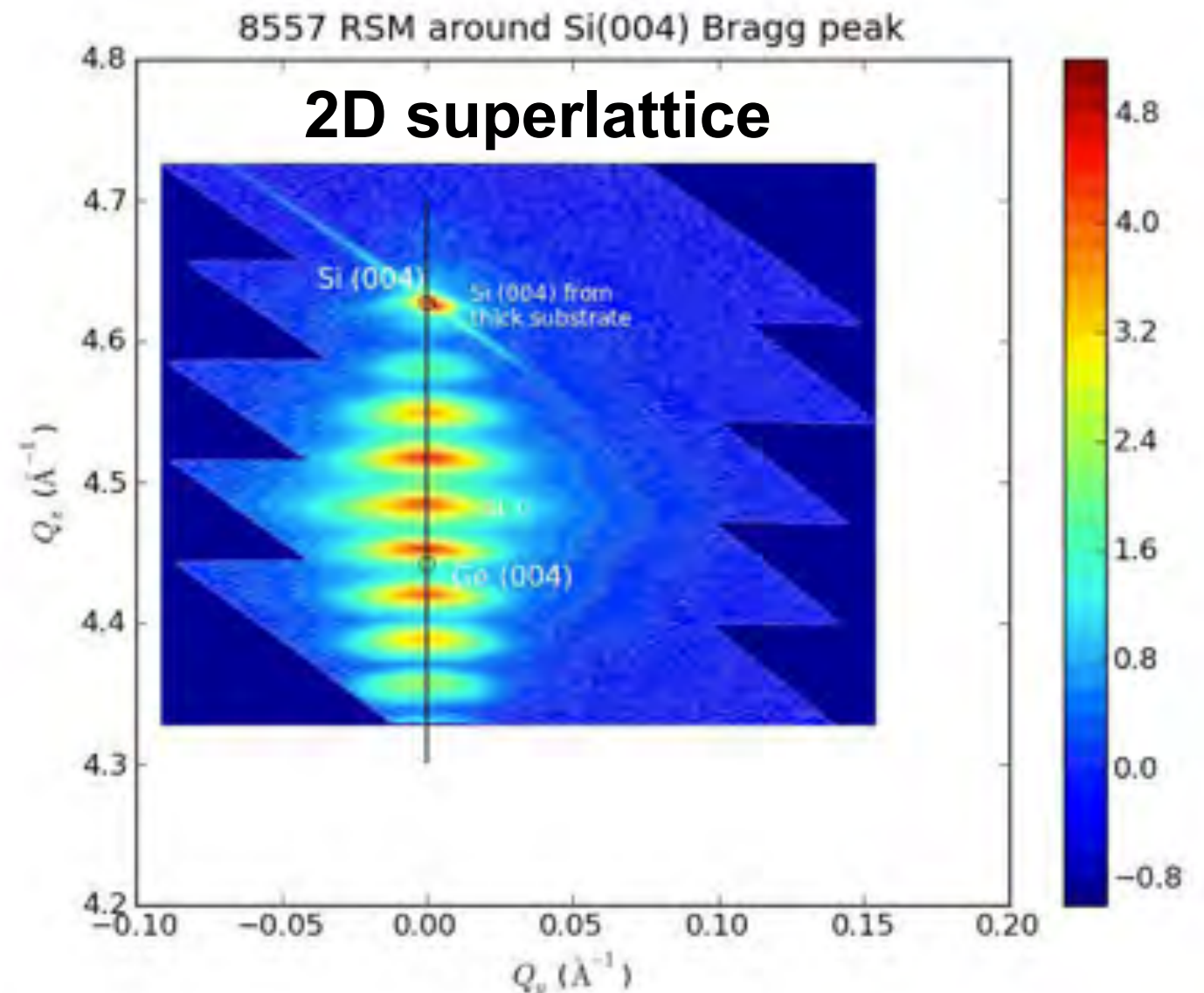
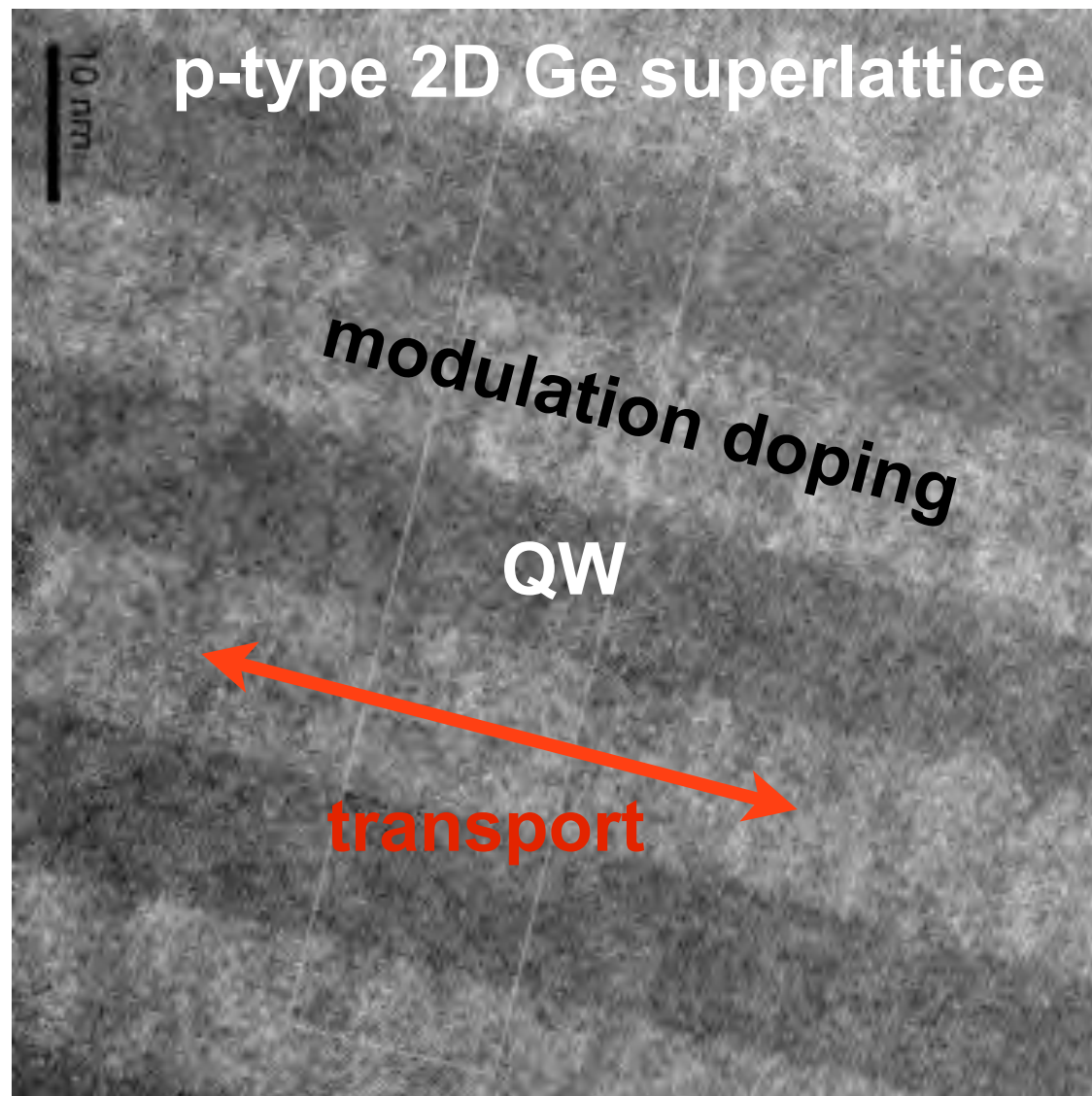
● Thermal conductivity most difficult

● Discussions with NPL on EC Metrology Programme



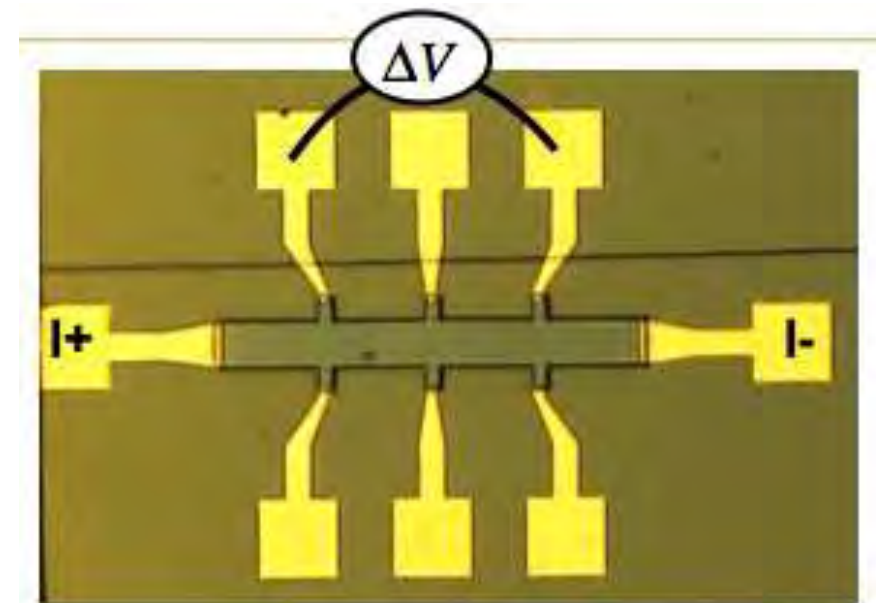
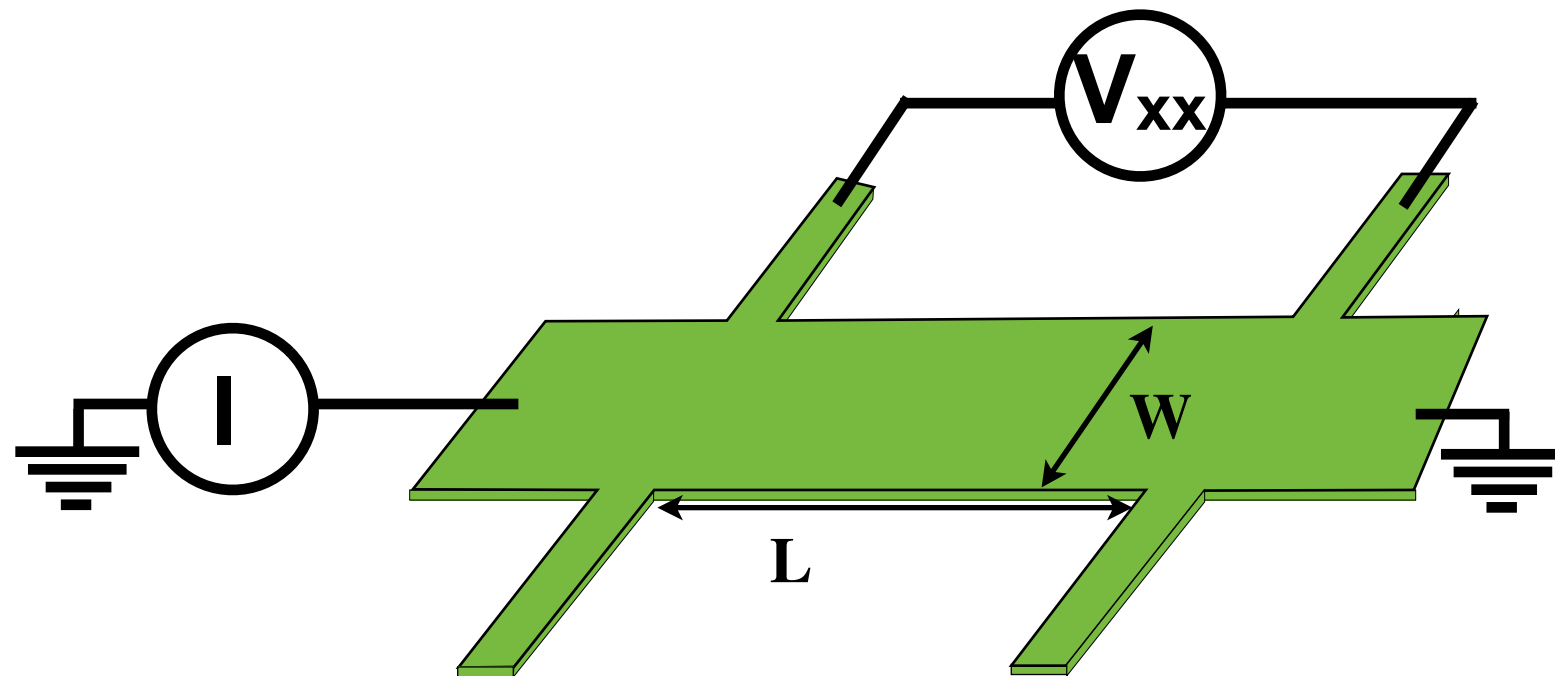


# 2D p-Ge Modulation Doped Structure 8557



- TEM & XRD characterisation of 2D modulation-doped superlattice designs

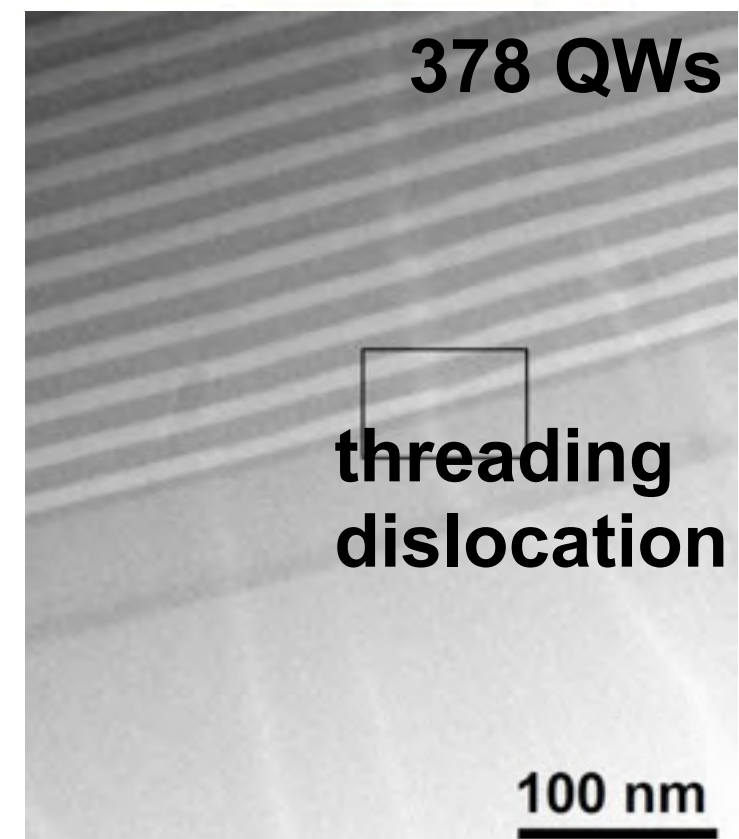
# Electrical Conductivity Measurements p-Ge



$$\sigma = \frac{IW}{V_{xx}L}$$

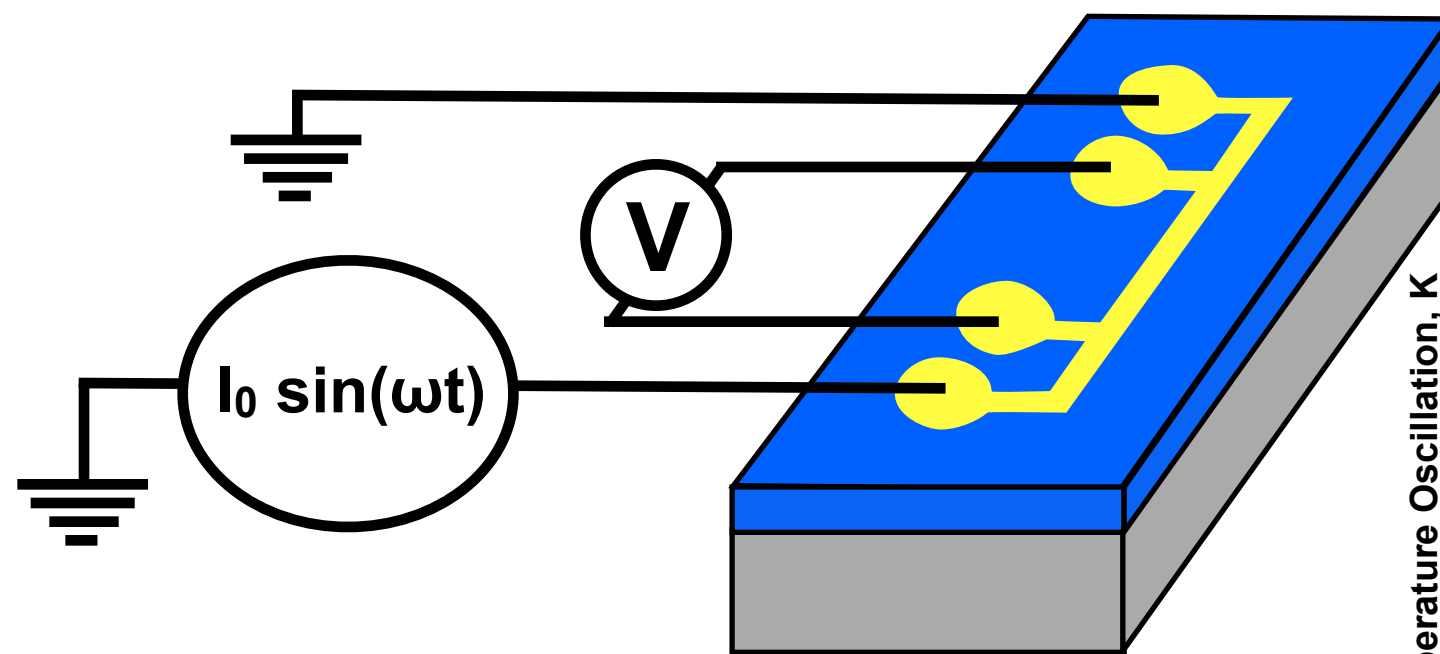
If  $L > 3W$  then  $\Delta\sigma < 10^{-3}$

$$\sigma = 118,000 \pm 15,000 \text{ S-m}$$



Most measured variations in  $\sigma$  related to non-uniformity of material

# Differential $3\omega$ Thermal Conductivity Measurement

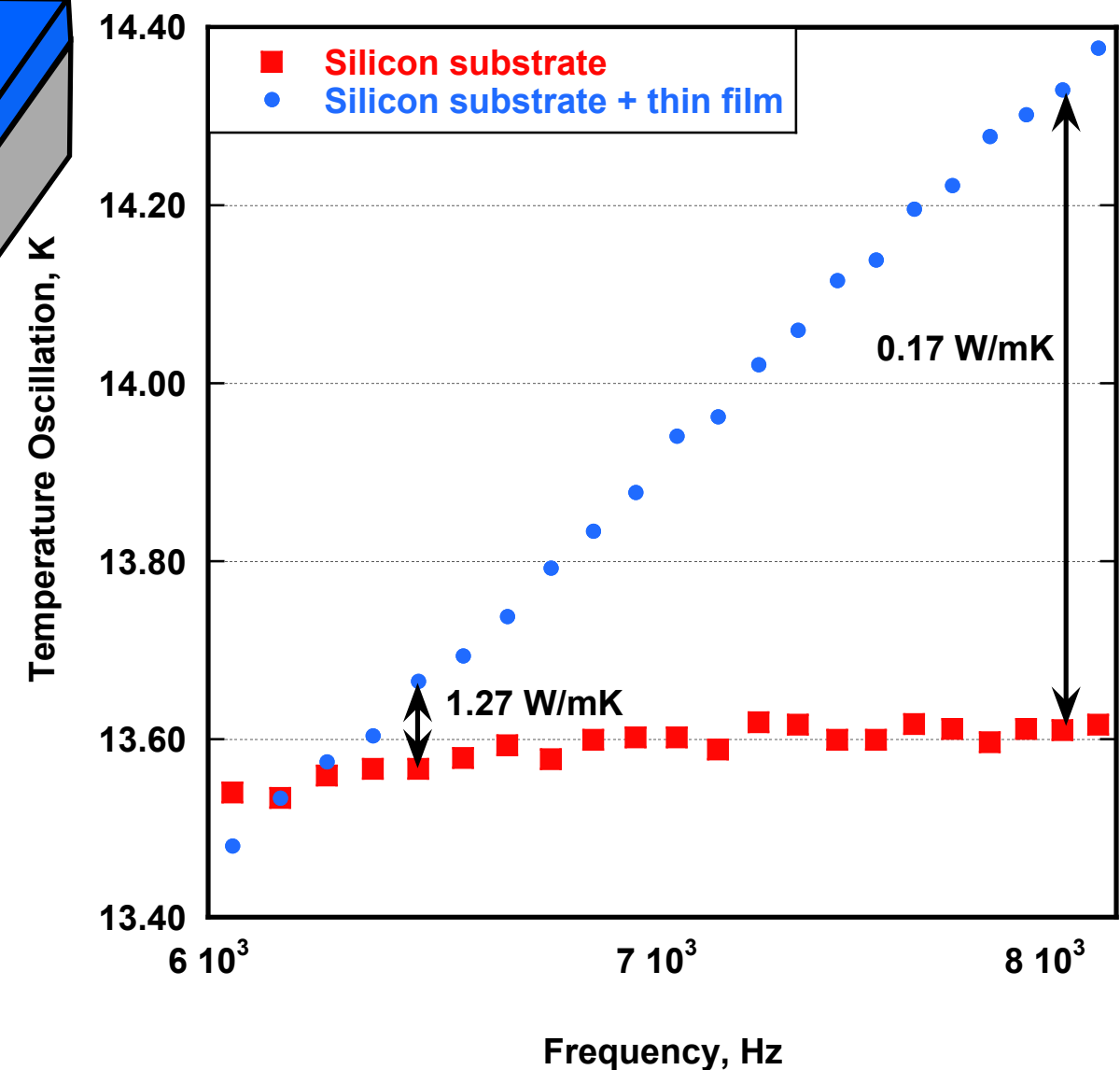
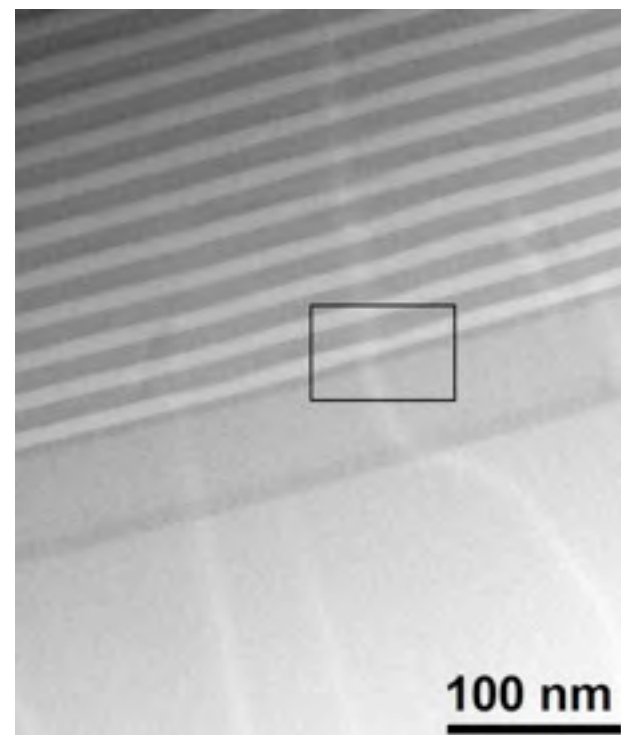


$$I \sim \omega$$

$$T \sim I^2 \sim 2\omega$$

$$R \sim T \sim 2\omega$$

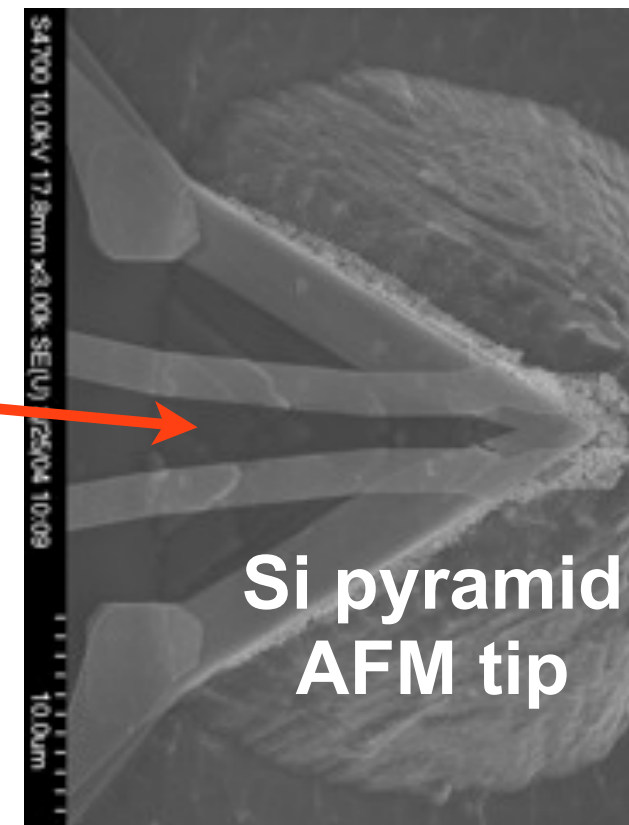
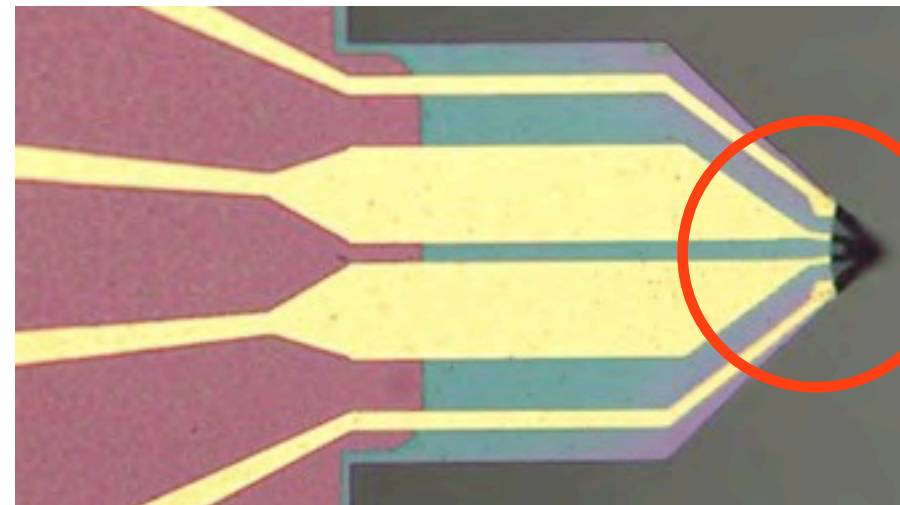
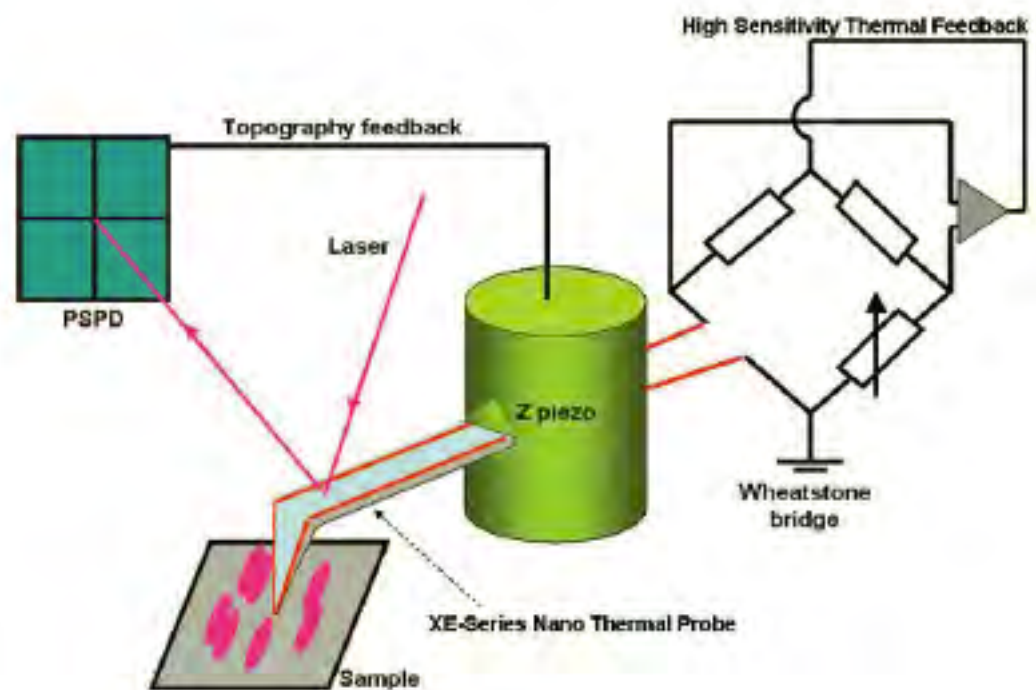
$$V = IR \sim 3\omega$$



**But  $3\omega$  technique requires homogenous layers !!!**

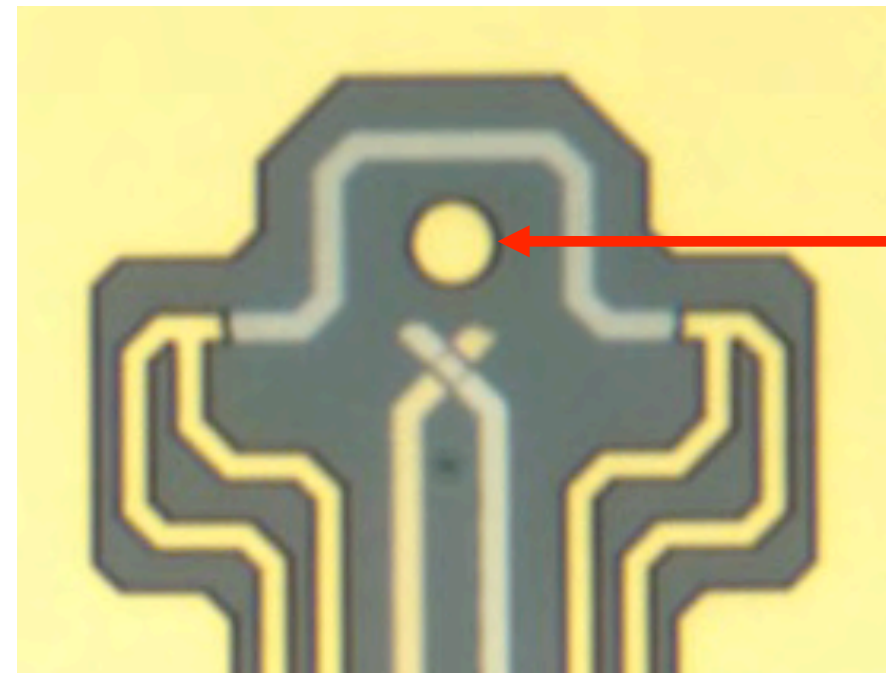
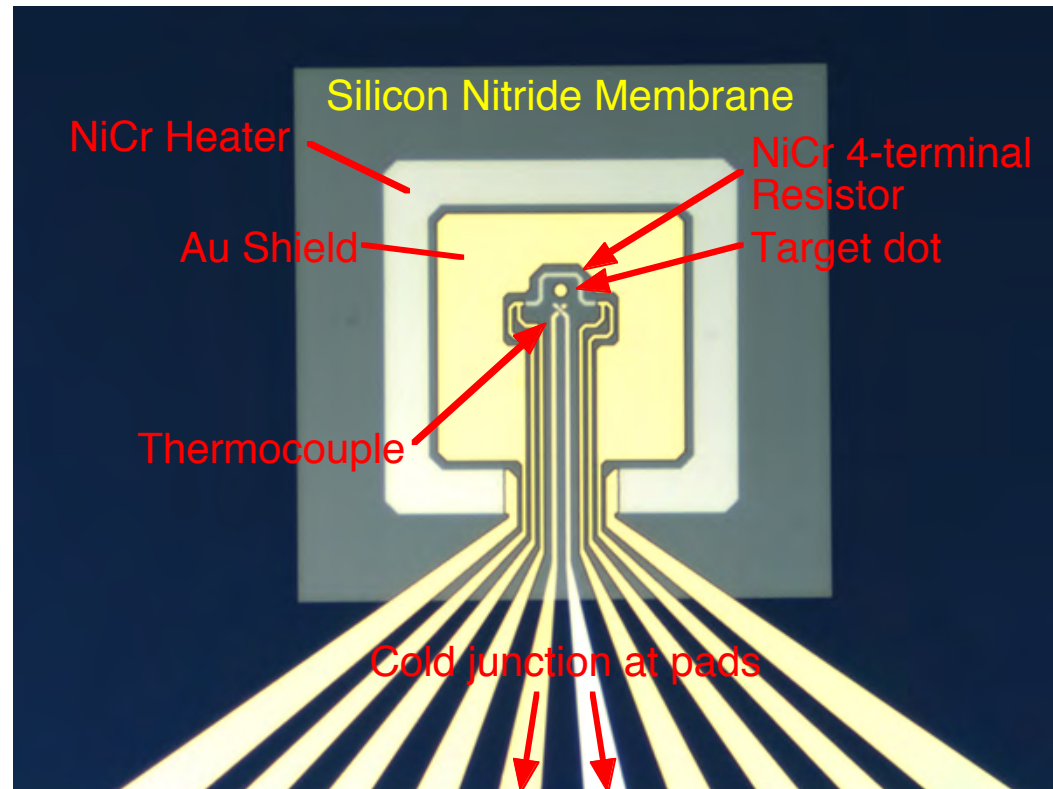


# Thermal Conductivity using Thermal AFM

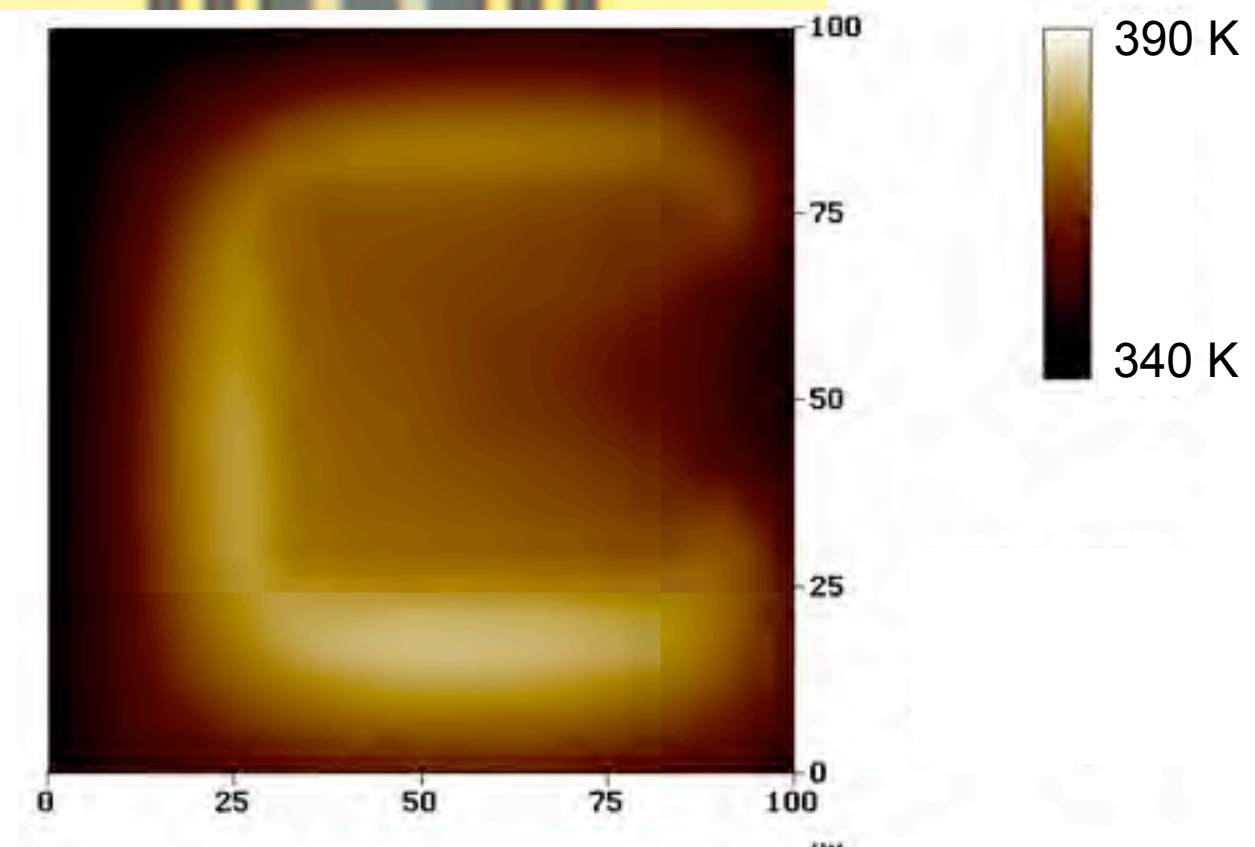
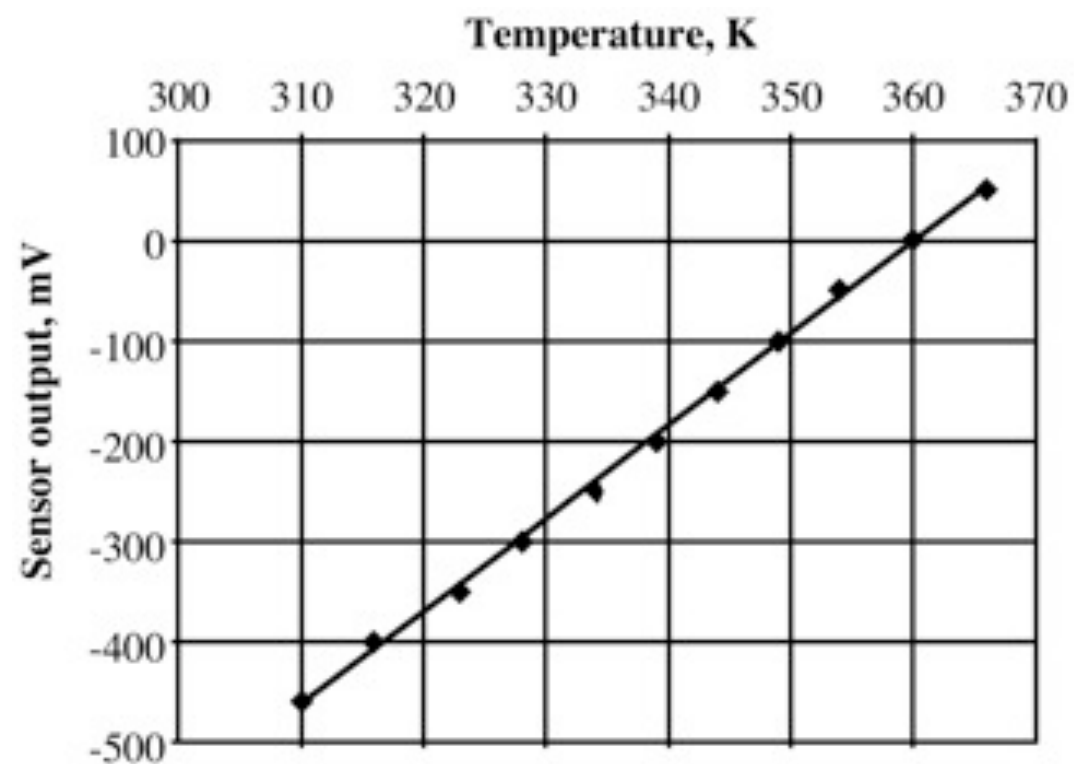


- **Spatial resolution < 100 nm (ideal for micro and nano structures)**
- **Temperature resolution to 0.1 K**
- **Direct temperature measurements (and  $3\omega$ )**

# Thermal AFM Calibration



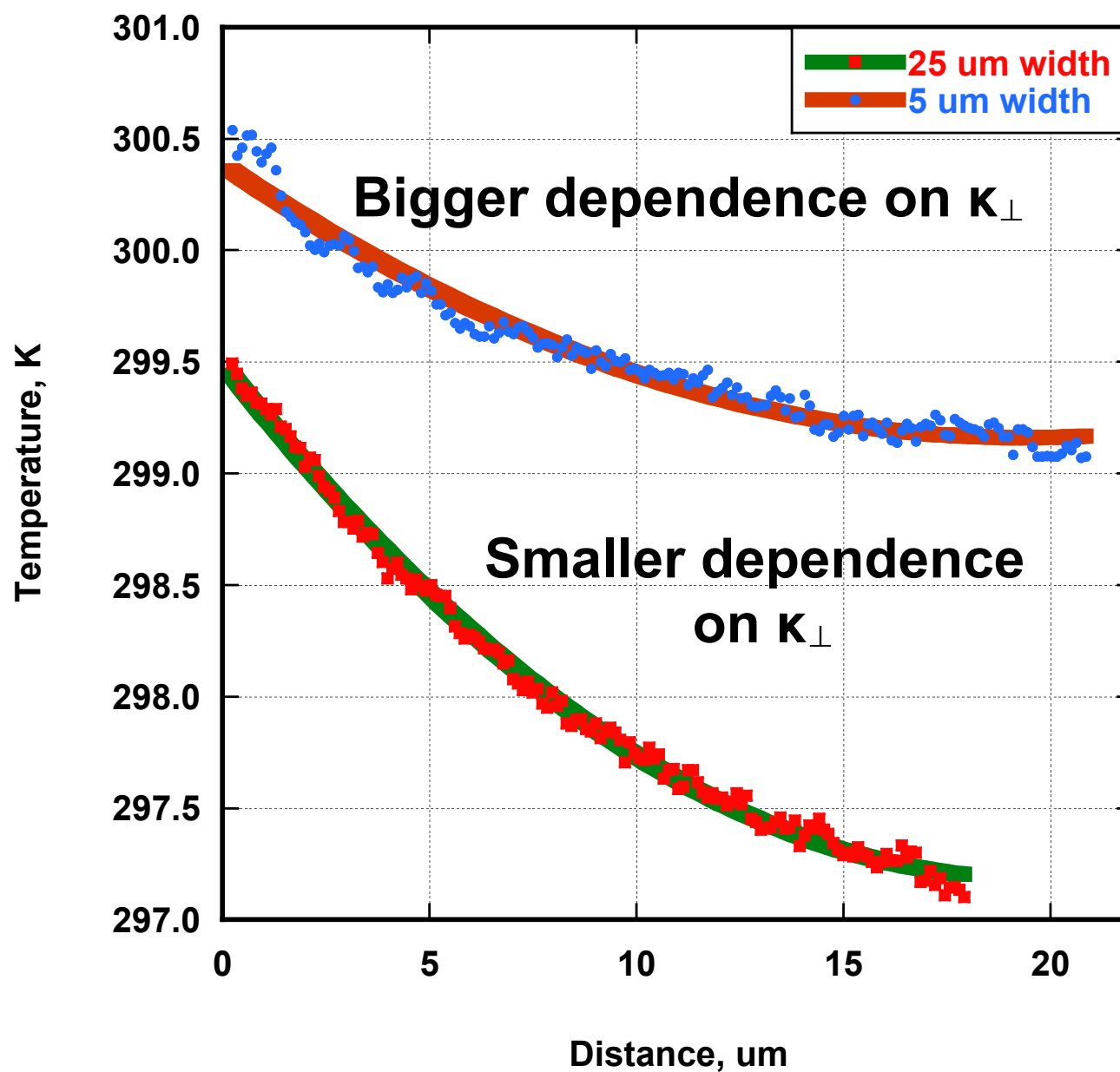
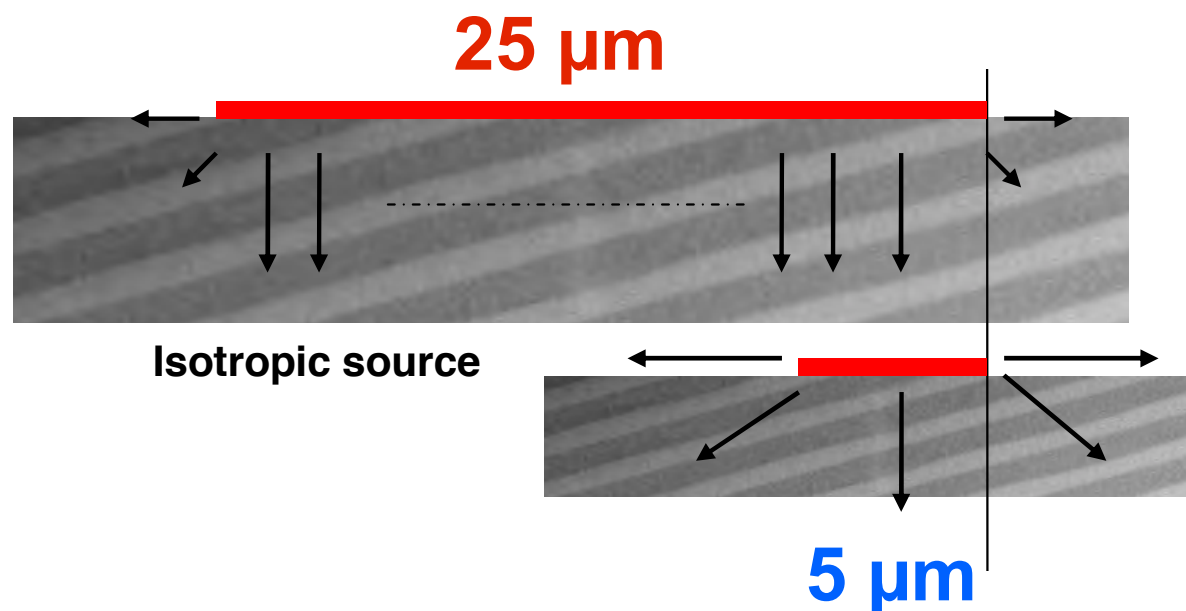
**Electrically isolated Au spot: isothermal with resistor**



*P. S. Dobson, et al., Rev. Sci. Inst. 76, 054901 (2006)*



# Thermal AFM Measurements p-Ge 8557



$$\kappa = 6.36 \pm 0.20 \text{ W/mK}$$

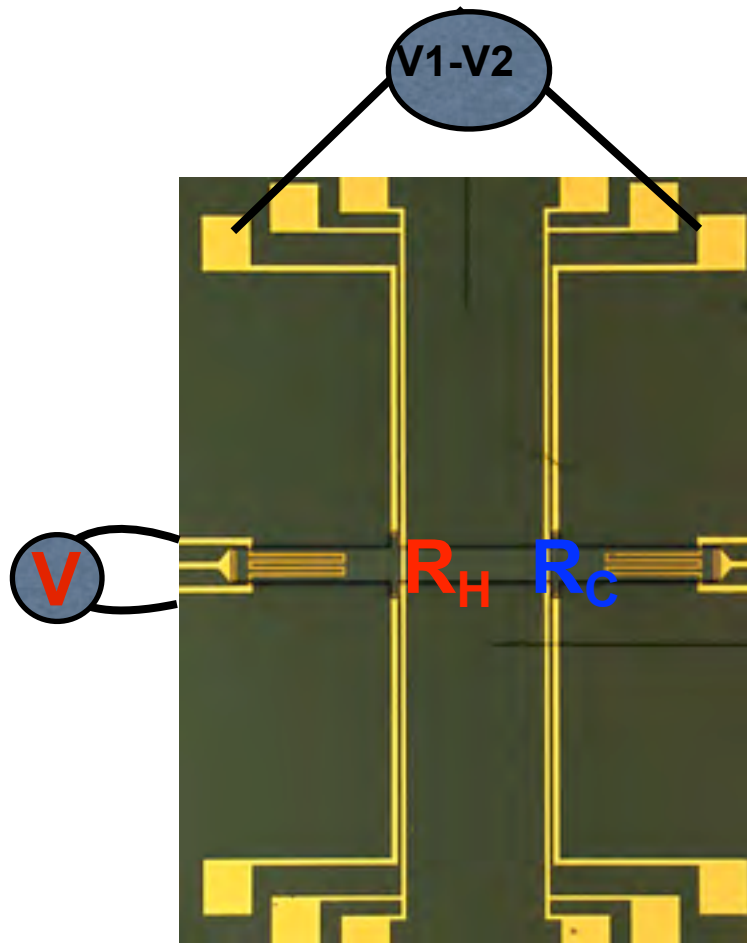
Voltage

Temperature vs position

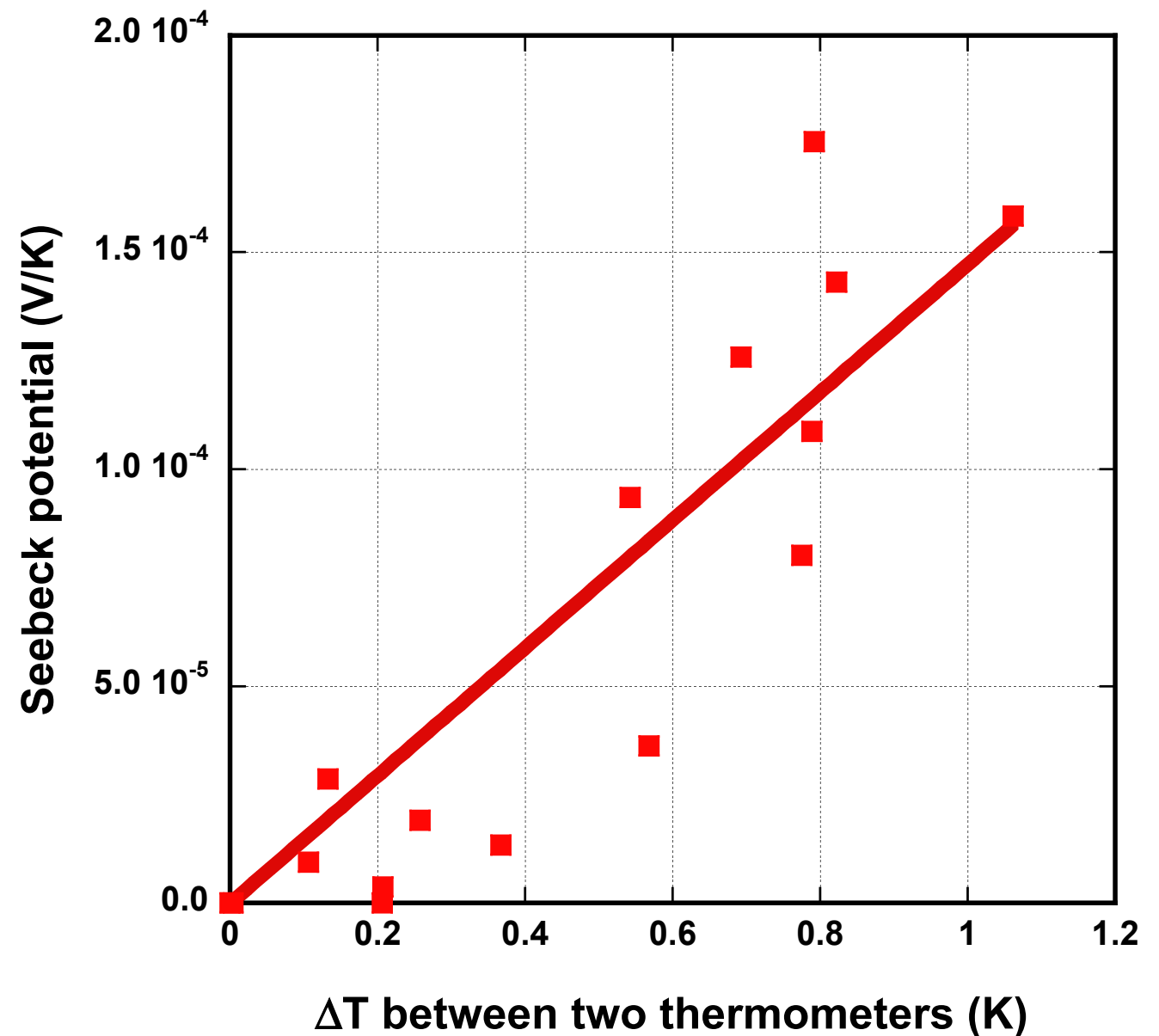
Calibrated thermocouple

+  
Johnson noise compensation

# Seebeck Coefficient Measurements



- Apply voltage through one heater
- Measure the  $\Delta V$  across bar
- Check
- Reverse the voltage
- Reverse the Bar

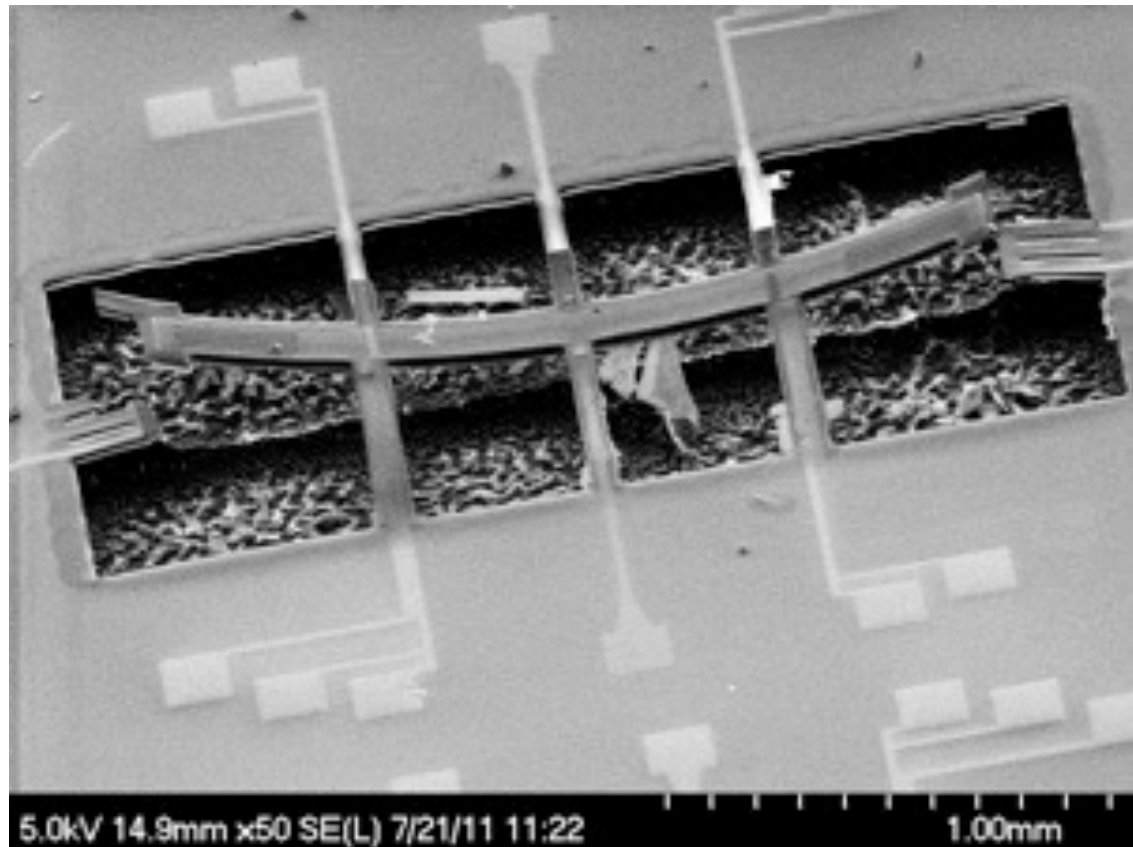


$$\alpha = 150 \pm 13 \mu\text{V/K}$$

Strong influence of the substrate: need to remove the substrate for feasible measurements

# SiGe Hall Bar with Substrate Removal

**Strain balancing required to make measurements of the thermal conductivity and Seebeck coefficient**

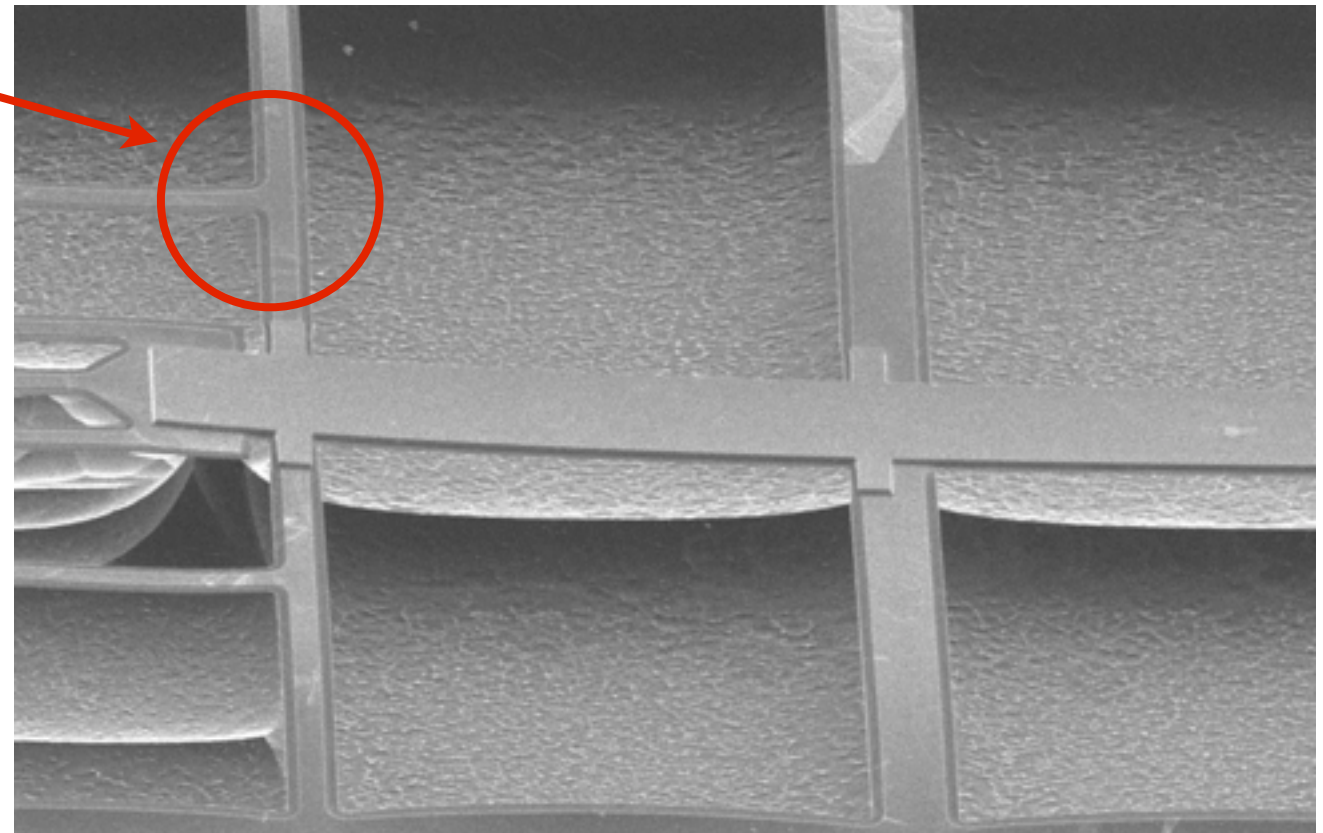
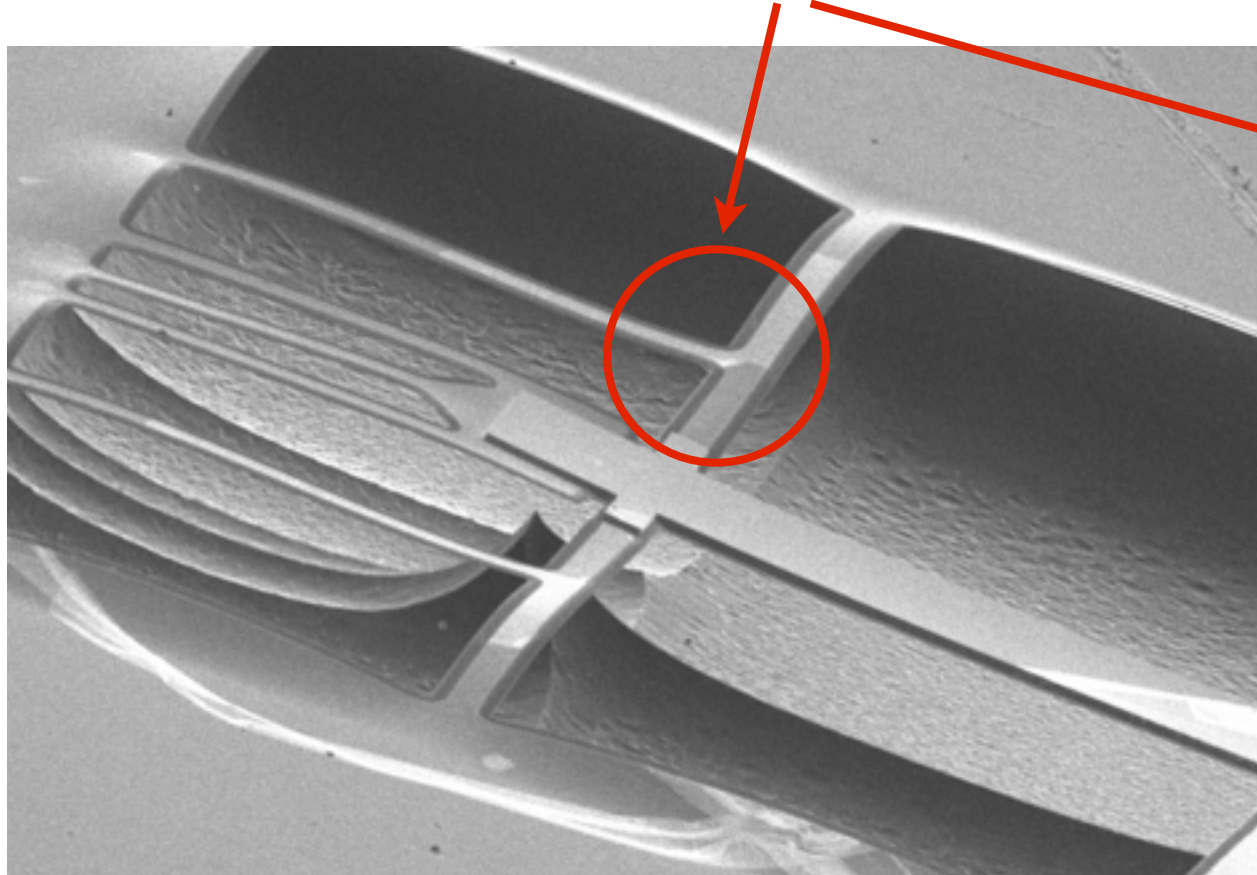


- Improvements in the material quality
- Scaling of the dimension of the Hall Bar (Length and width)
- Change in the geometry of the Hall Bar- Silica support structure:
- Elimination corners, sharp edges, increase in the number of supports

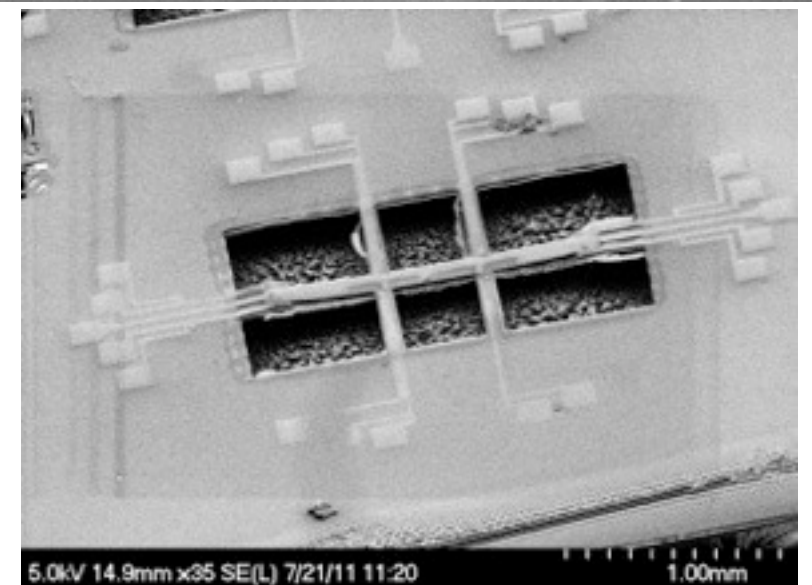


# Seebeck Coefficient / Thermopower

- Large Hall Bars (about 1.5 and 2 mm long)
- Adding some **mechanical** strength to the actual devices.

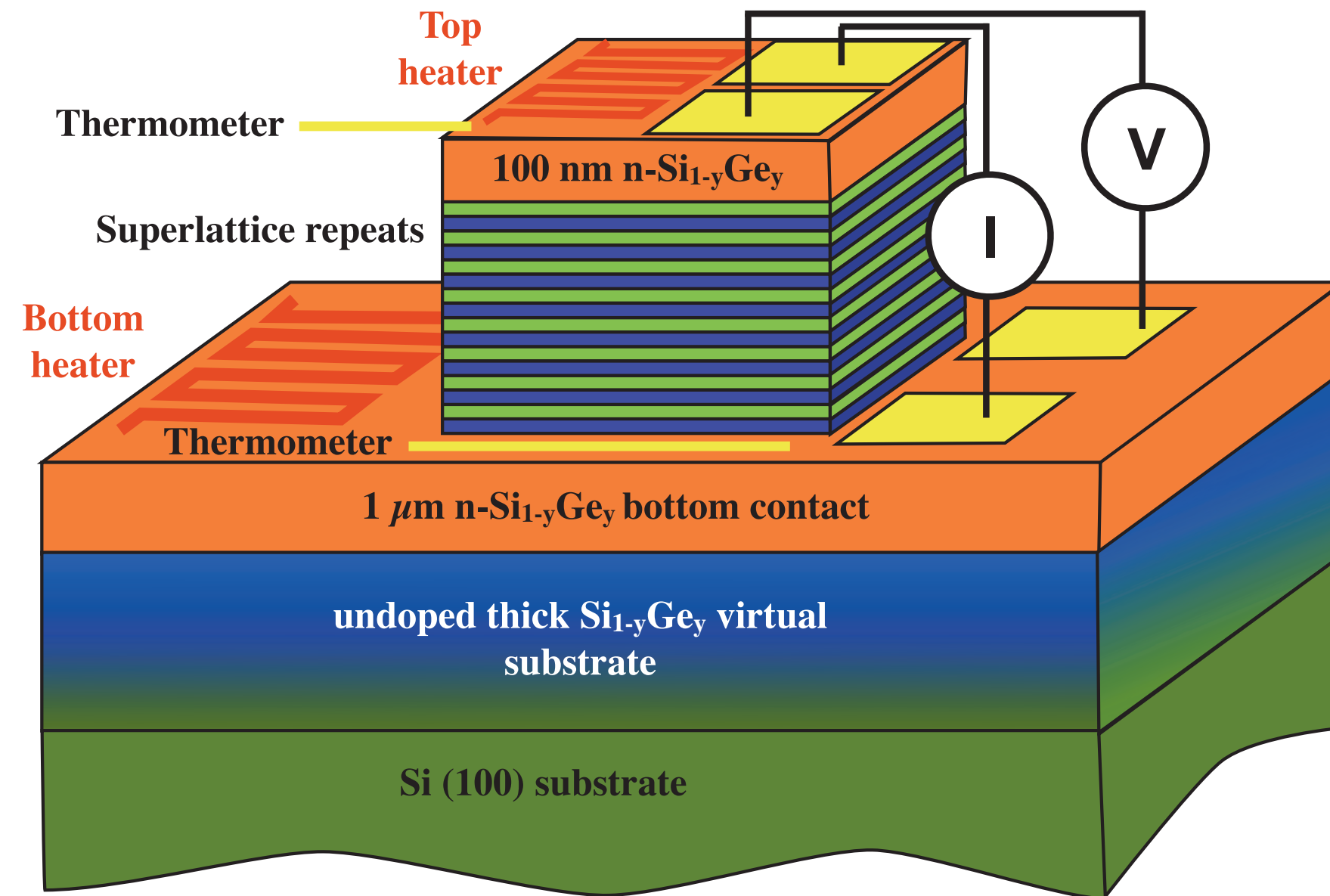


- Patterning **new shorter Hall Bars** to help the curvature of the membranes.



# ZT Measurements of Vertical Devices

## ZT Device Schematic Diagram



## Potential enhancements:

- Seebeck from low dimensions
- Phonon scattering barriers
- Phonon bandgaps / stationary phonons



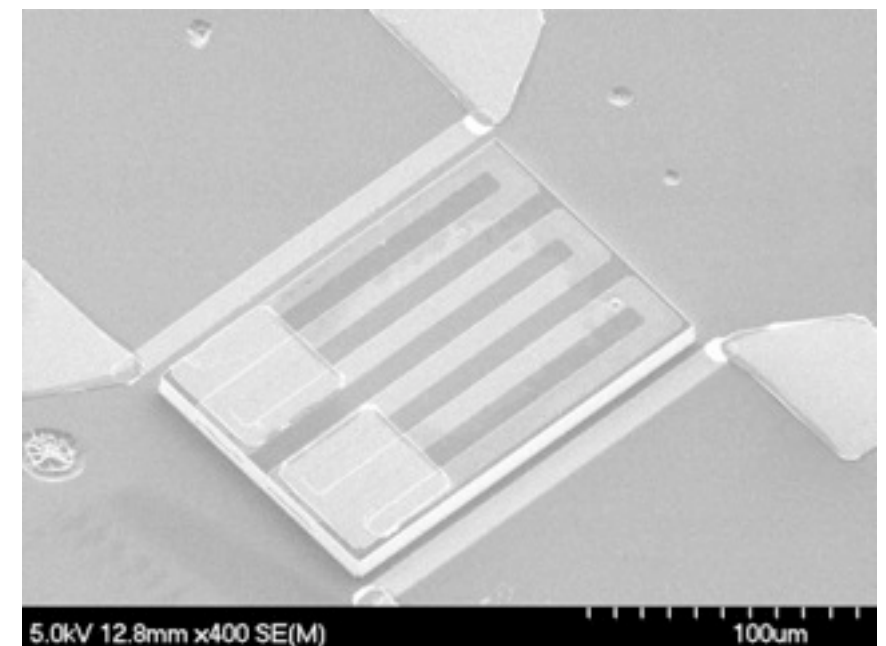
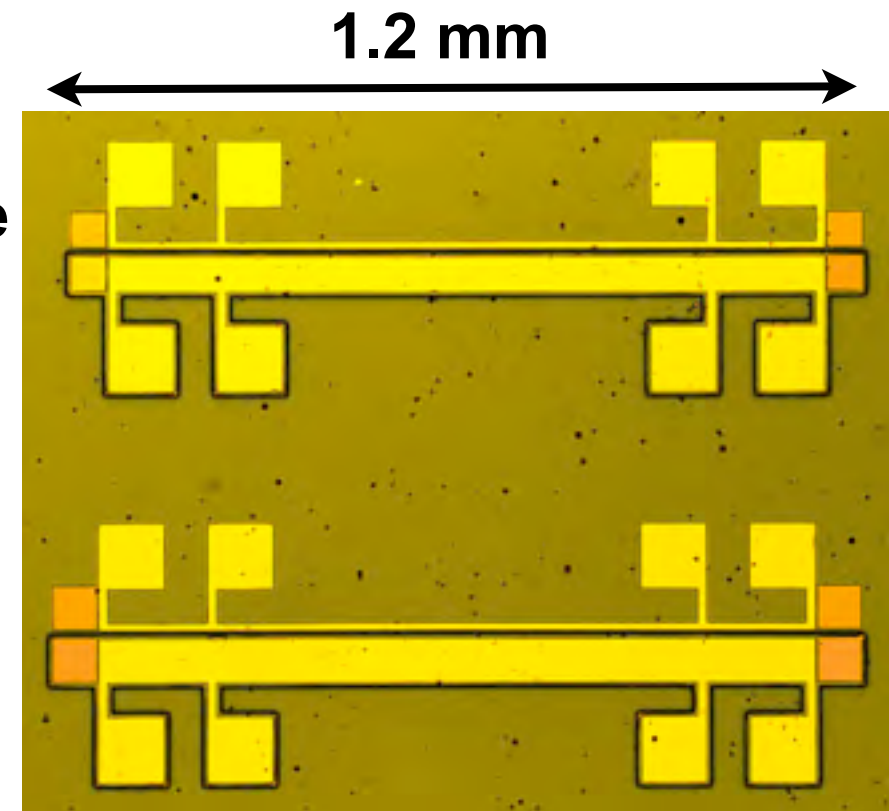
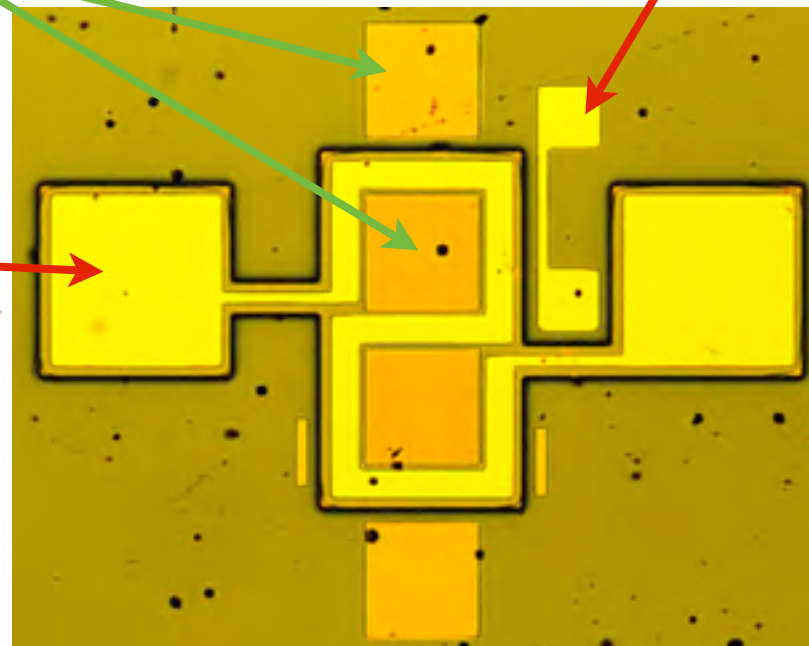
# Vertical devices

- Different geometries to evaluate vertical properties of the material.
- Heaters used as thermometers to reduce the top surface area of the Mesa -> reduced thermal gradients across in plane surfaces.
- Homogeneous heat flux along out-of-plane direction. Temperature cross calibration using thermal AFM

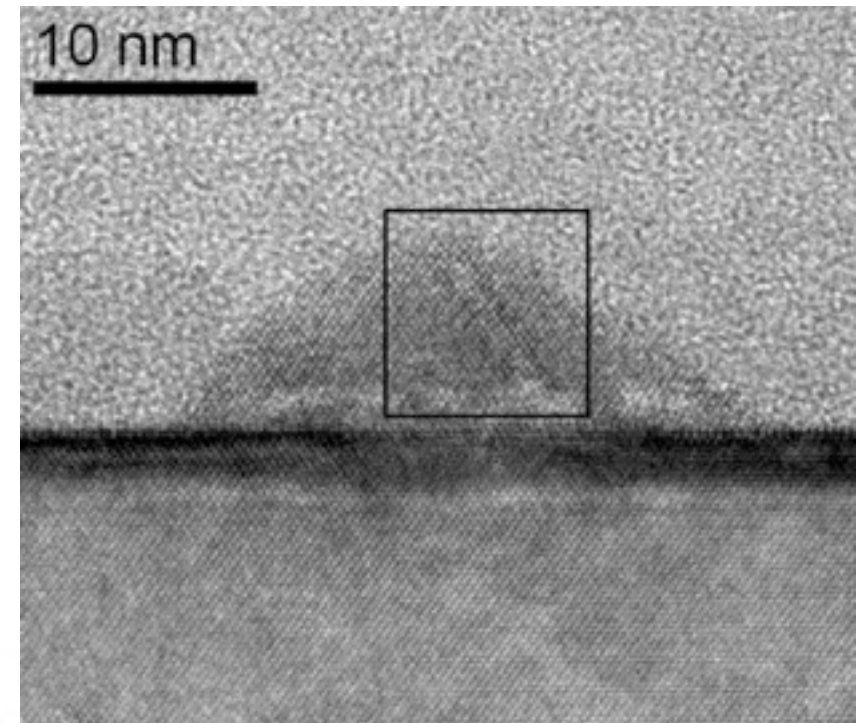
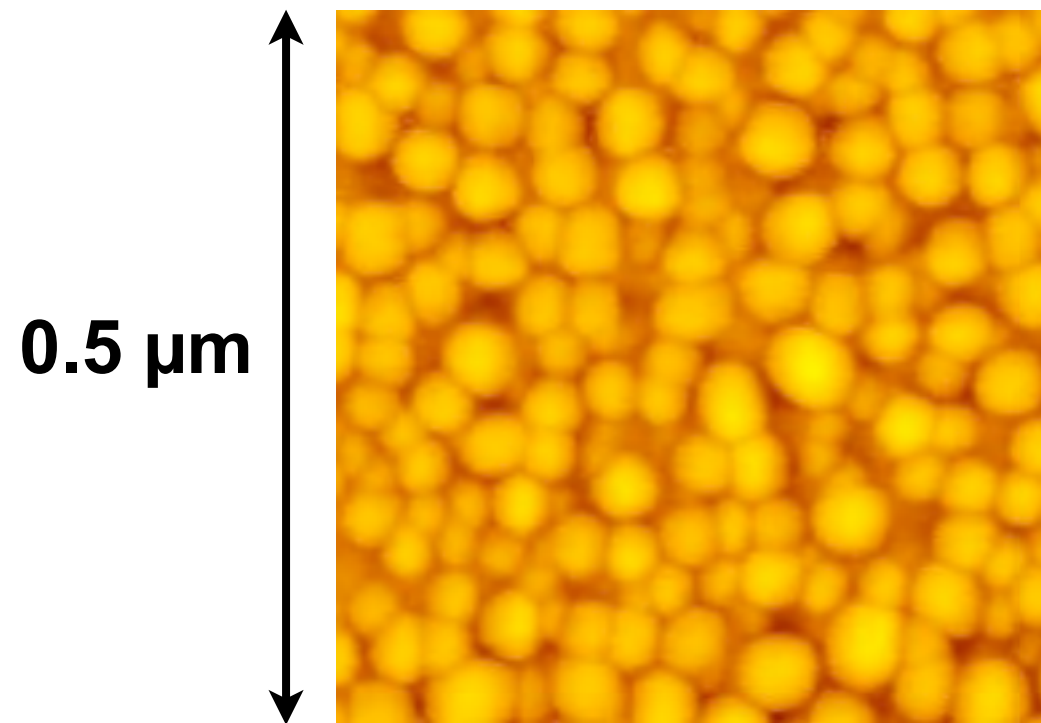
Nickel-Silicide Ohmic contacts

Bottom Platinum thermometer

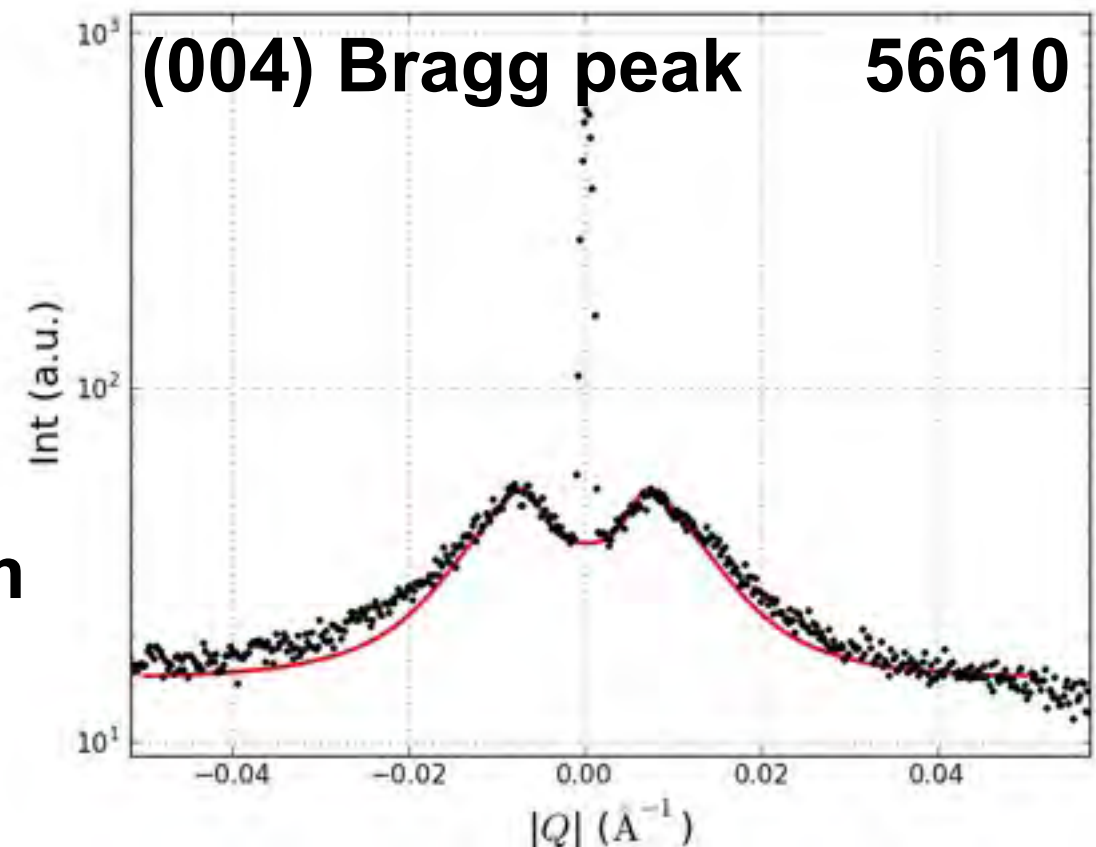
Top Platinum heater/thermometer



# 0D Ge Quantum Dots



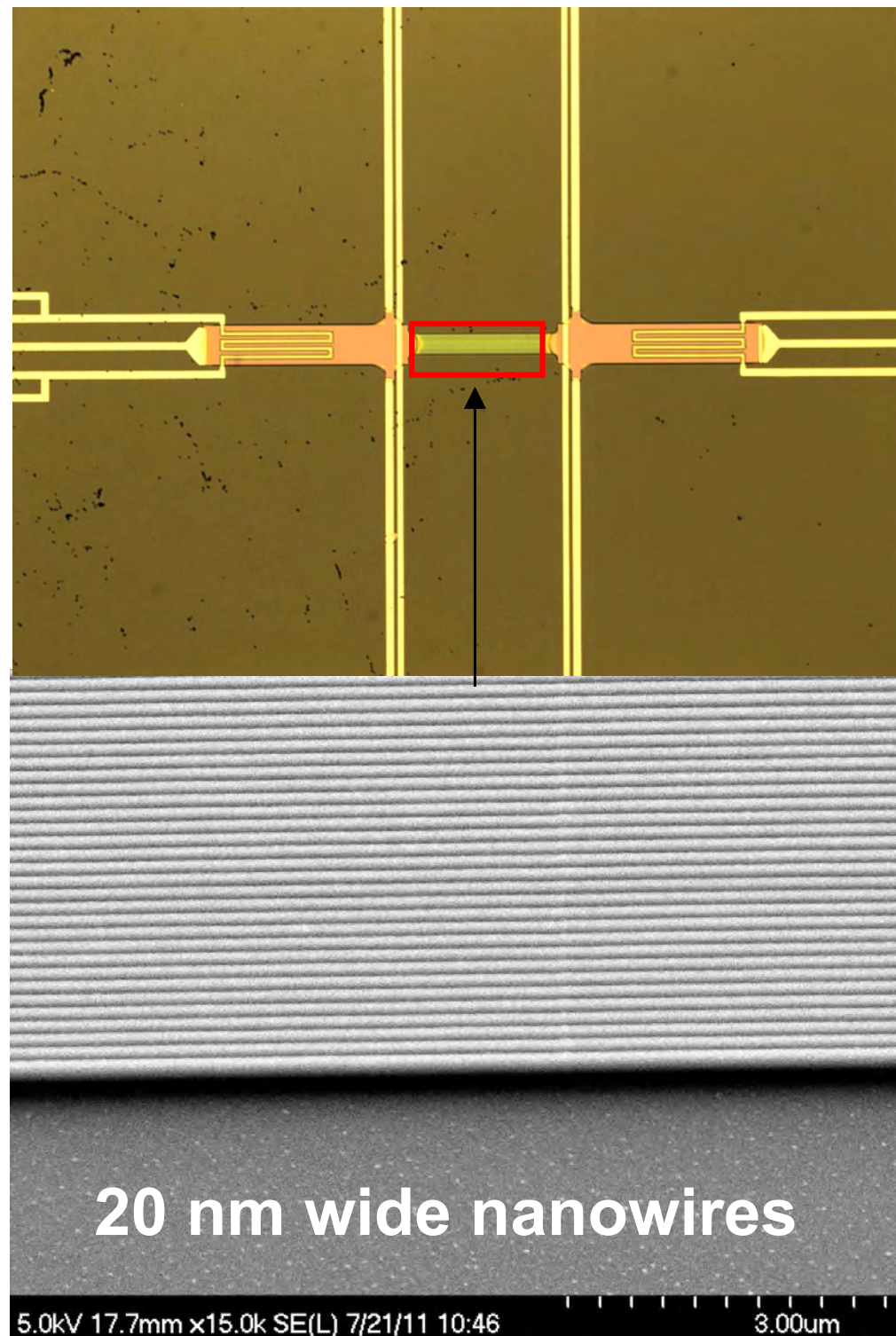
- Phonon scatterers
- XRD mean dot size  $8 \pm 5$  nm
- XRD mean dot spacing  $14 \pm 14$  nm
- i.e. uncorrelated dots



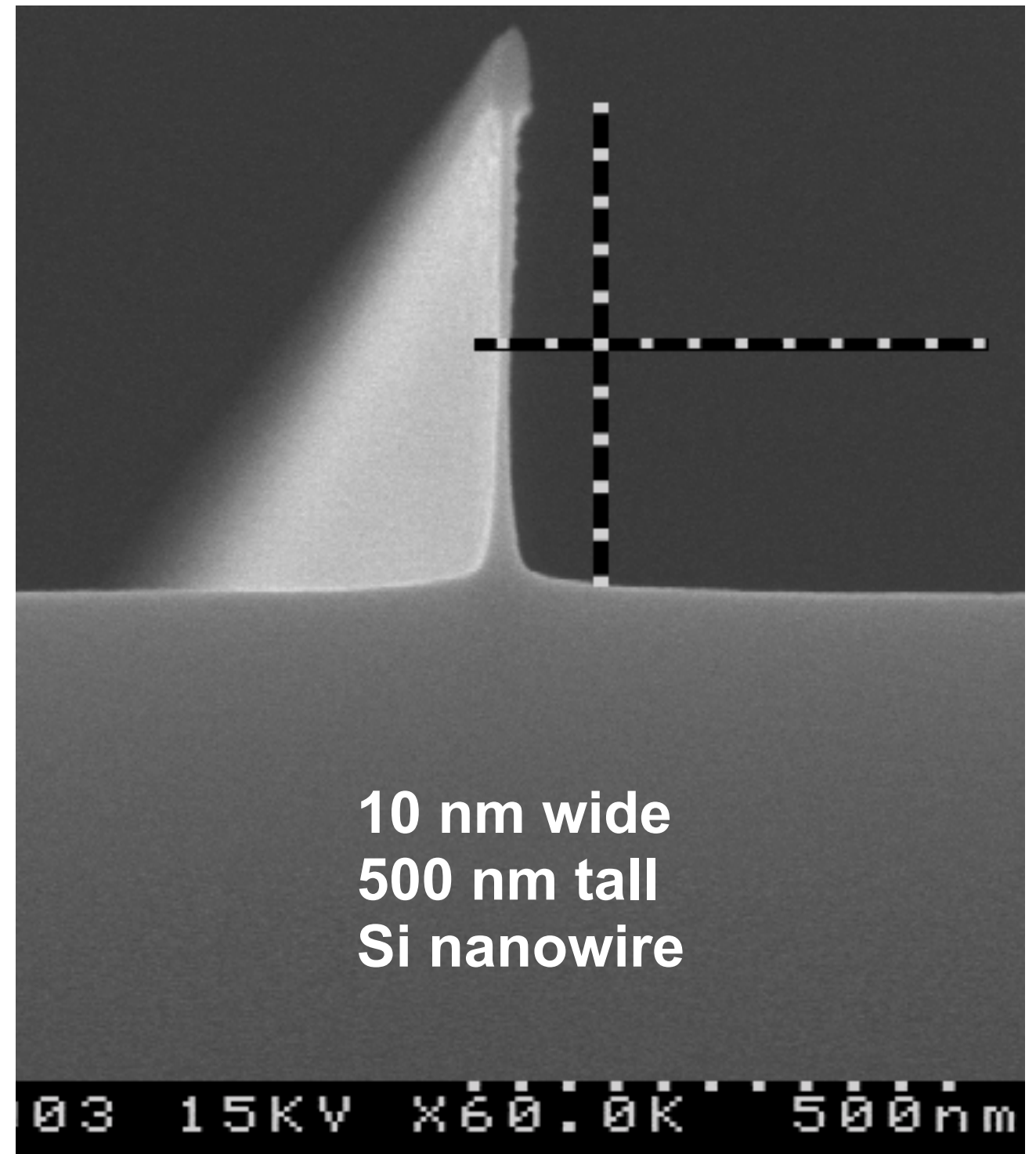


# 1D Si Nanowires

## Lateral Nanowires

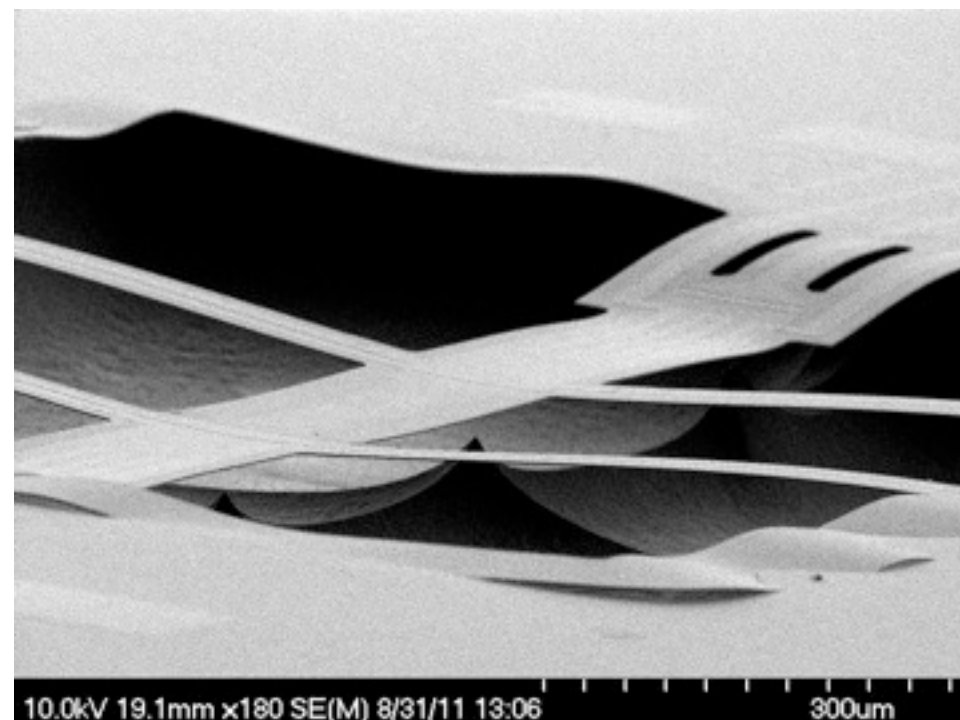
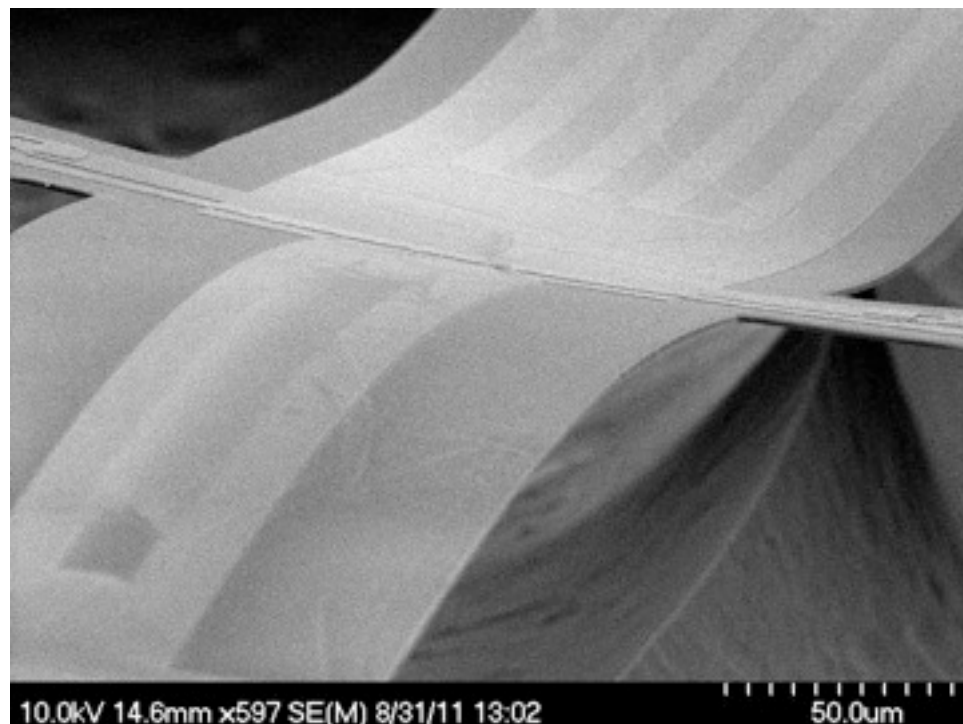
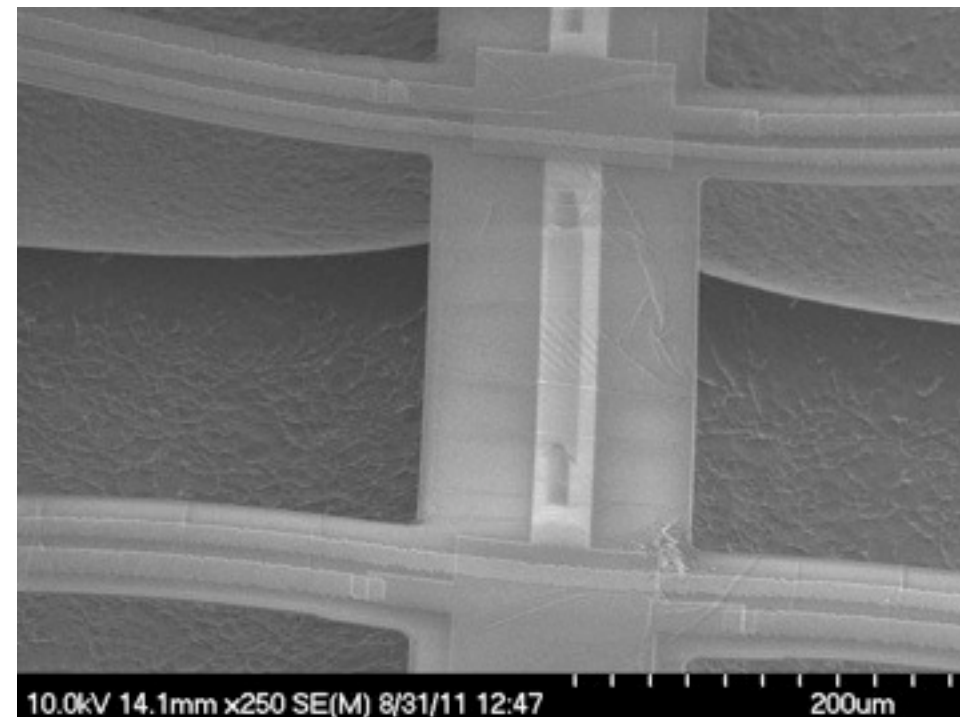
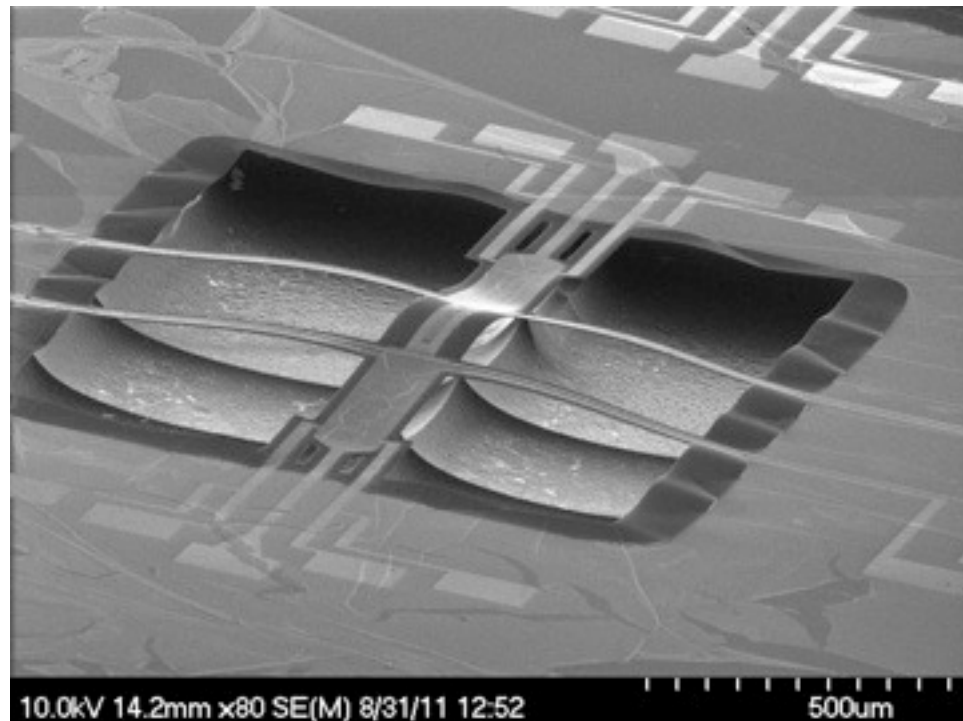


## Vertical Nanowires





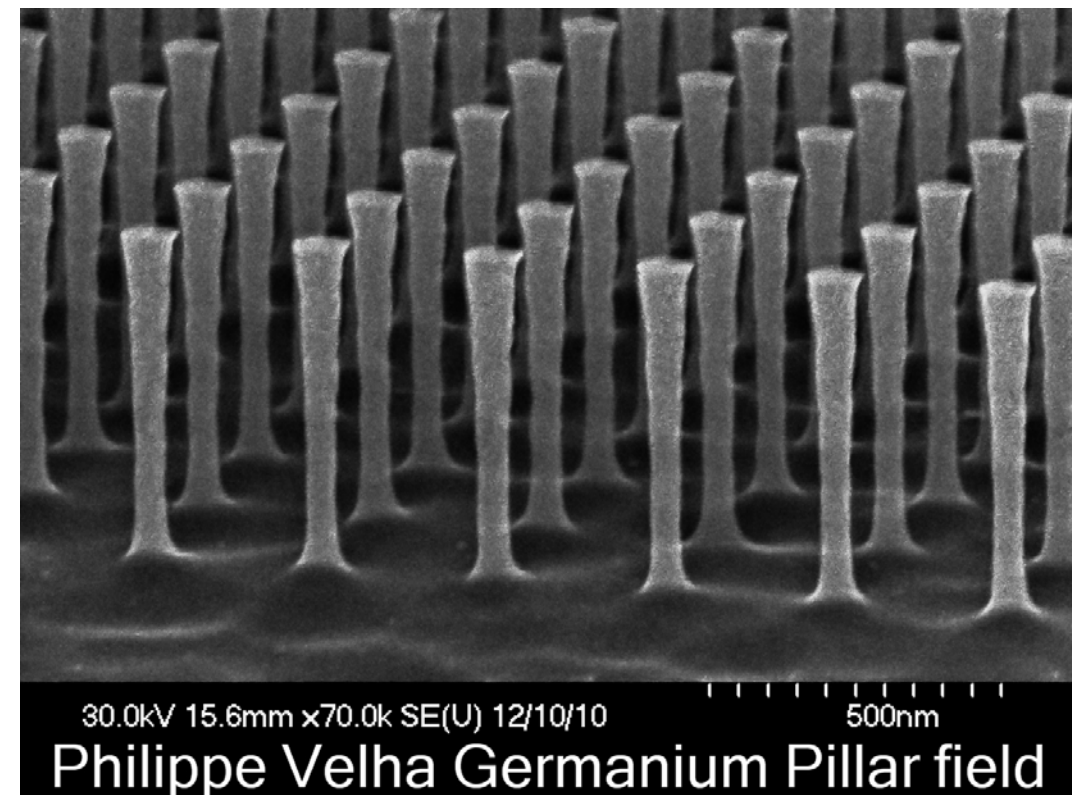
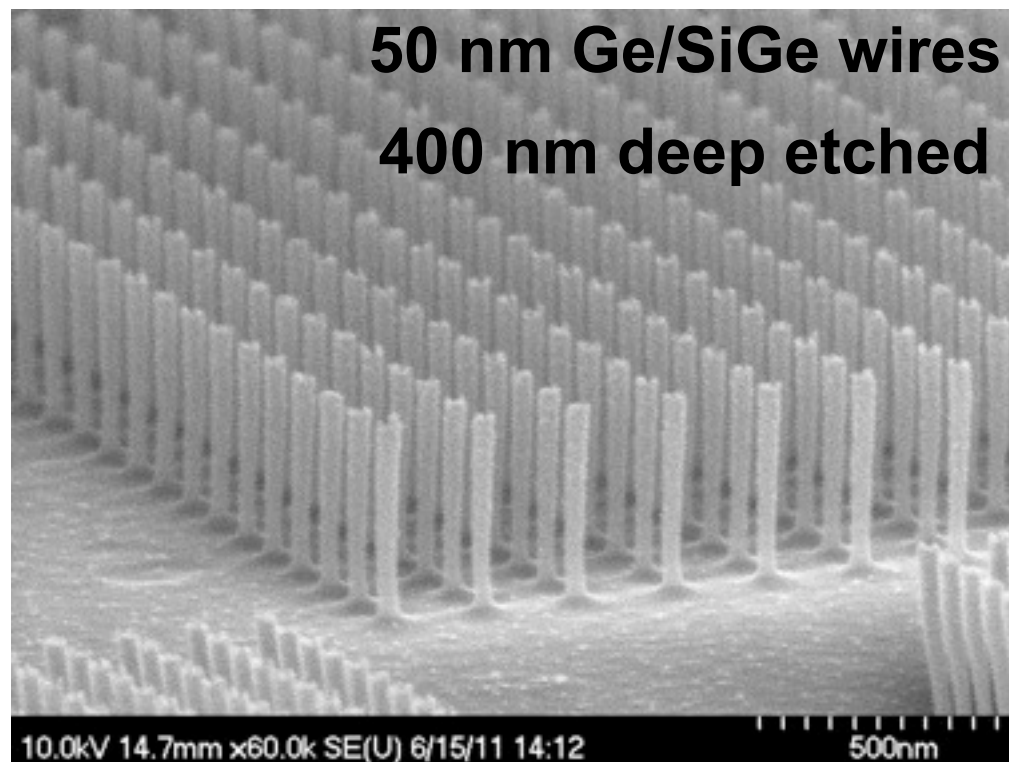
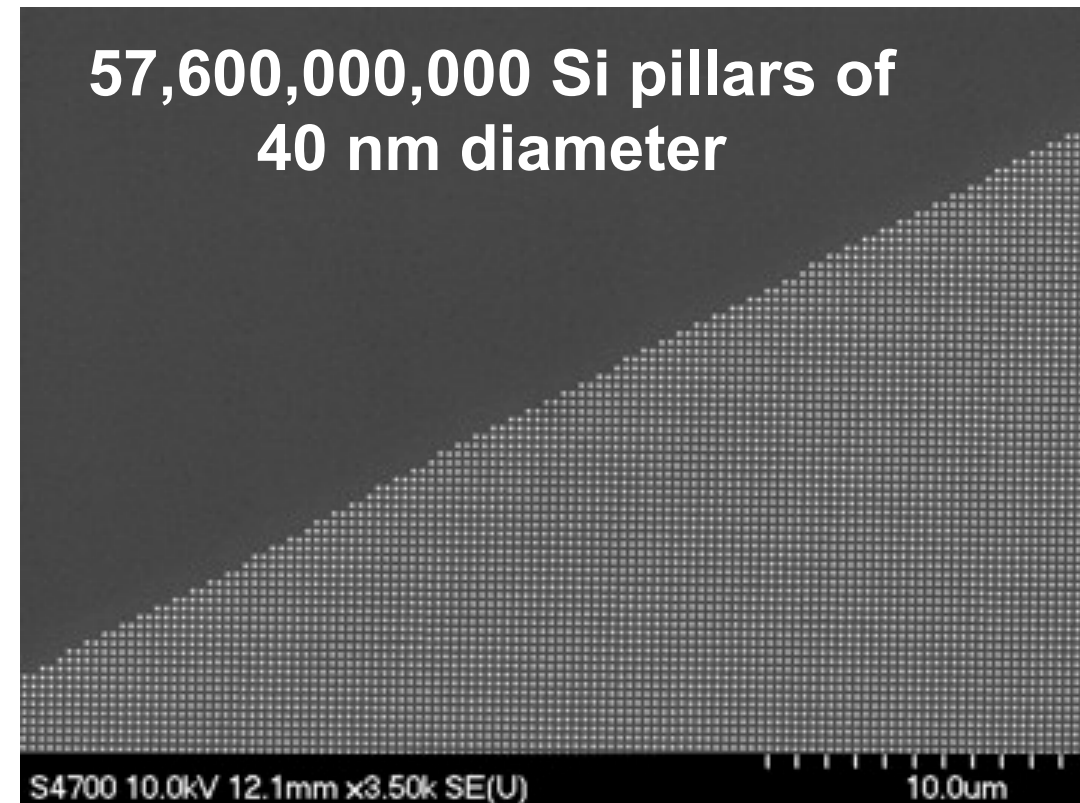
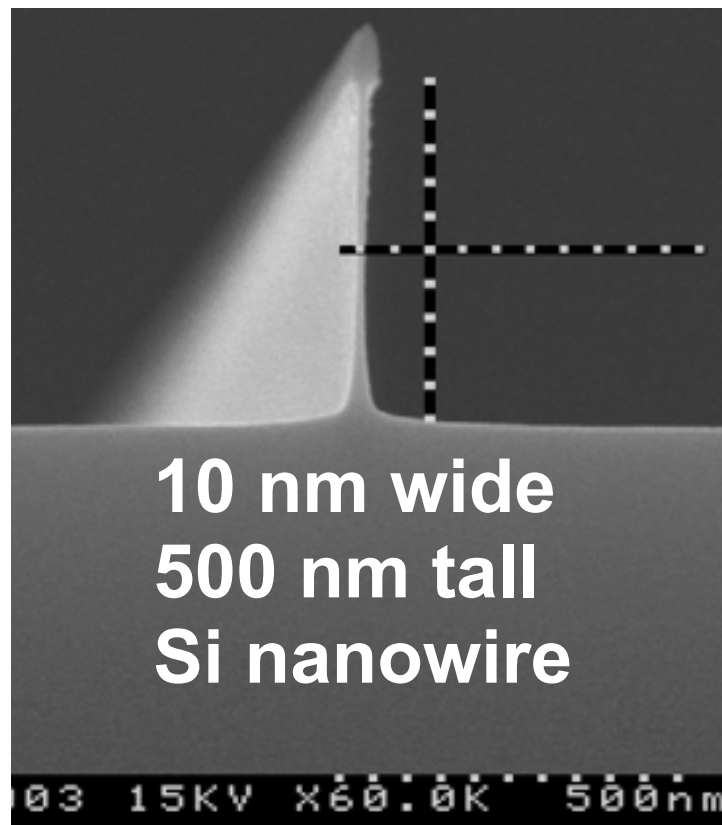
# 100 x 20 nm Wide Si Nanowires in Suspended Hall Bar



**Proof of concept: The structure are feasible → Technology**



# Si Nanowires: Practical 1D enhancements?





# Summary

- **Si/SiGe heterostructures for engineered electron & phonon transport towards enhanced thermoelectrics**
- **Accurate thermal measurements difficult → standards?**
- **Many thermal measurement techniques inaccurate**
- **<http://www.greensilicon.eu/GREENSilicon/index.html>**

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**Tel:- +44 141 330 5219**